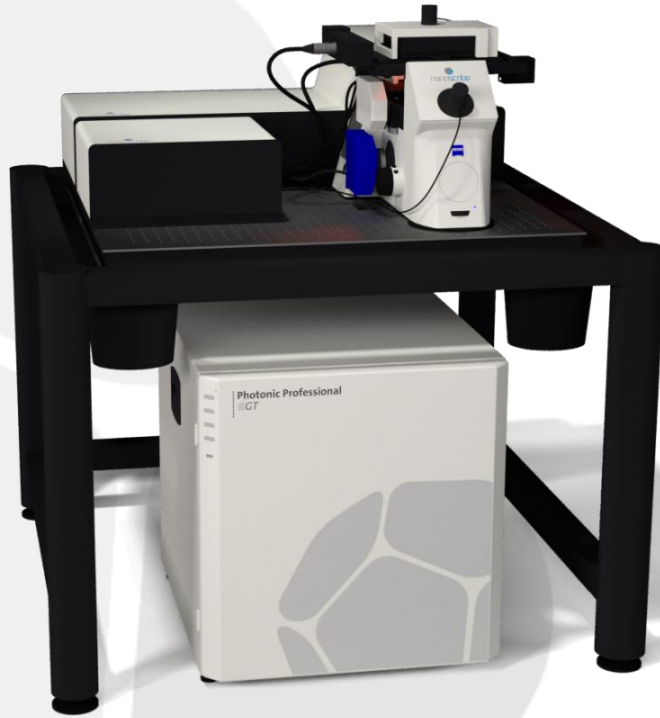


3D μ -Printing by Direct Laser Writing



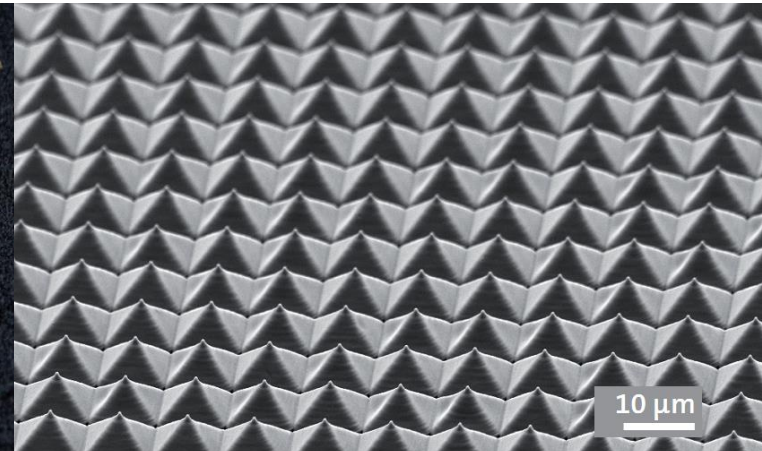
euspen

micro/nano manufacturing workshop
Karlsruhe Institute of Technology (KIT)

Nanoscribe GmbH

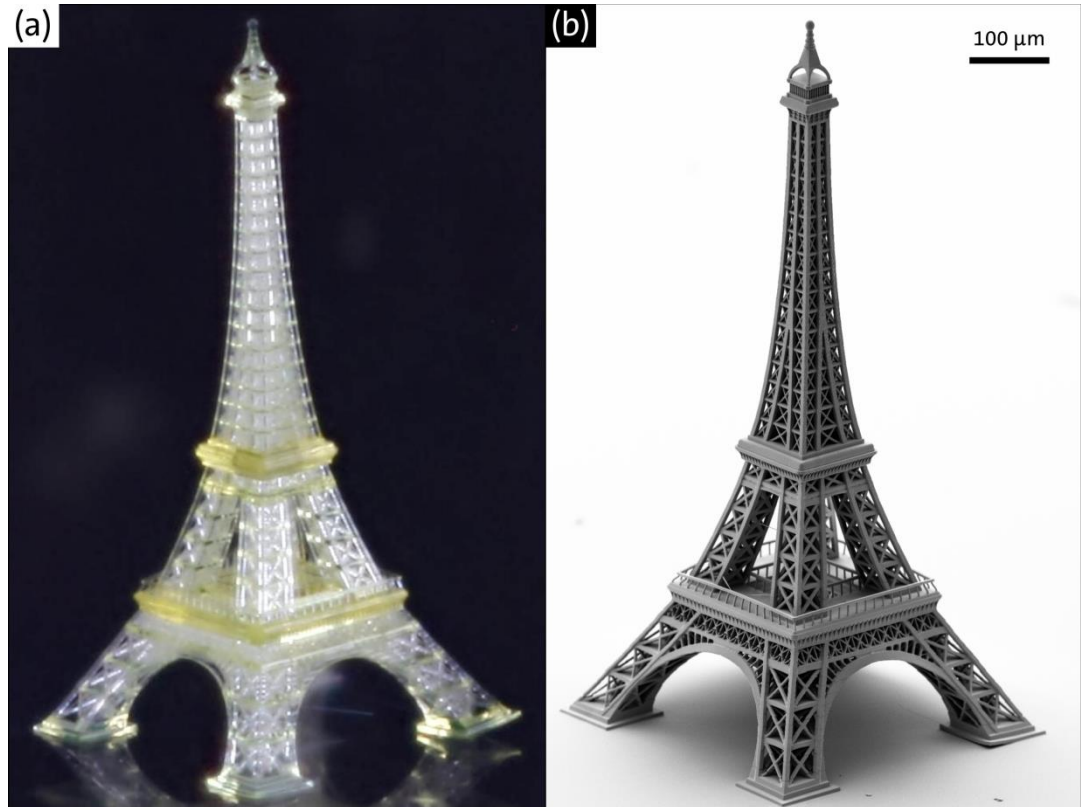
Martin Hermatschweiler, CEO

November 28th, 2013



Overview

- Introduction: Nanoscribe GmbH
- Technology: Direct Laser Writing
- Materials
 - Photoresists
 - Casting processes
- Applications
 - Photonics
 - Cell Biology
 - Microfluidics
 - Optical Telecom
 - Biomimetics
 - Micromechanics
- Summary



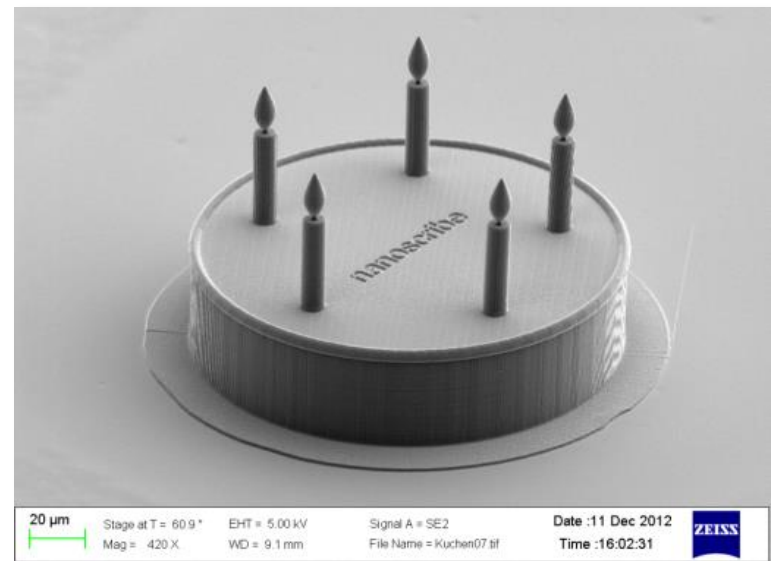
Who We Are ...

Company History:

- Spin-off from the Karlsruhe Institute of Technology (KIT) group: Prof. Dr. Martin Wegener
- 2007: Foundation
- >50 systems installed worldwide
- 27 employees + 2 students

Products:

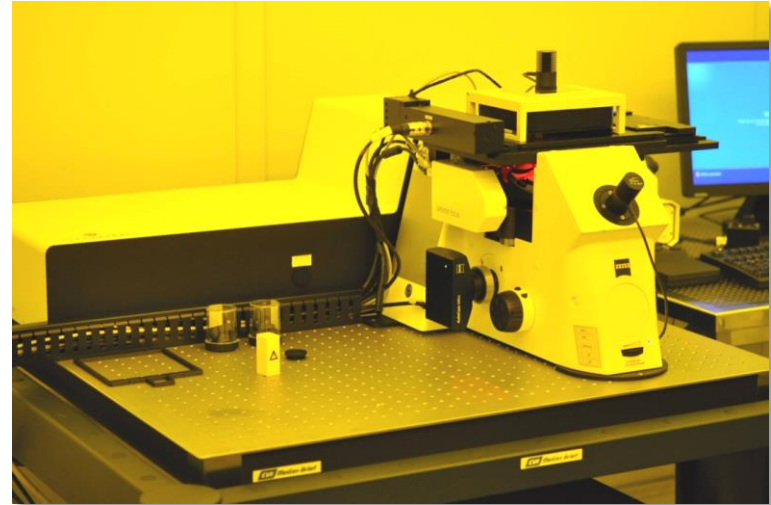
- 3D laser lithography systems
- Photoresists



What We Do ...

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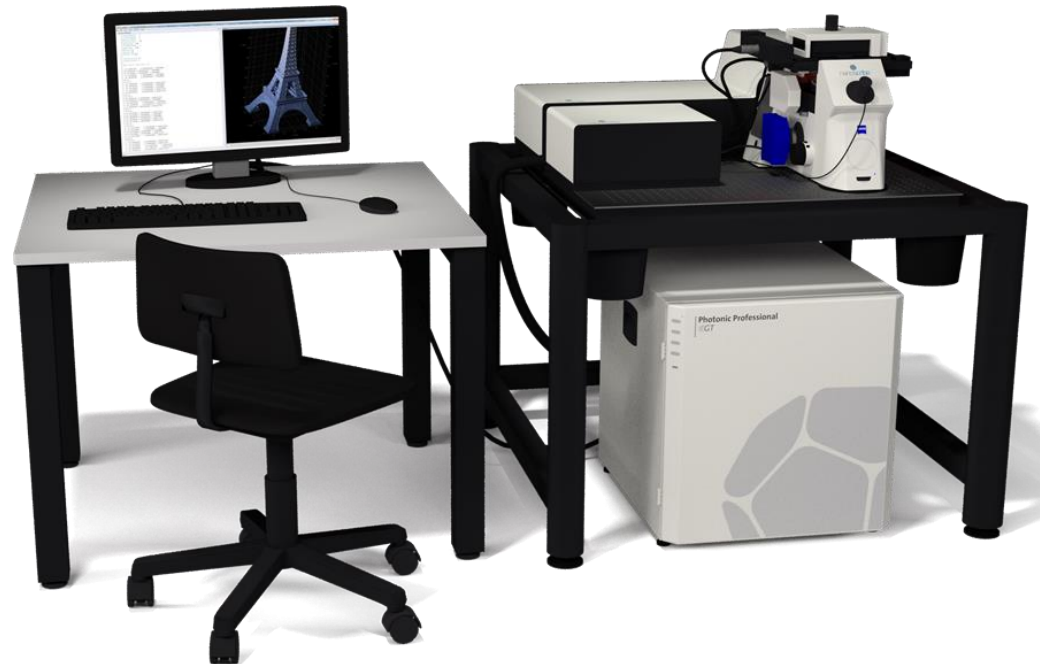
Products:

- 3D laser lithography systems
- Photoresists

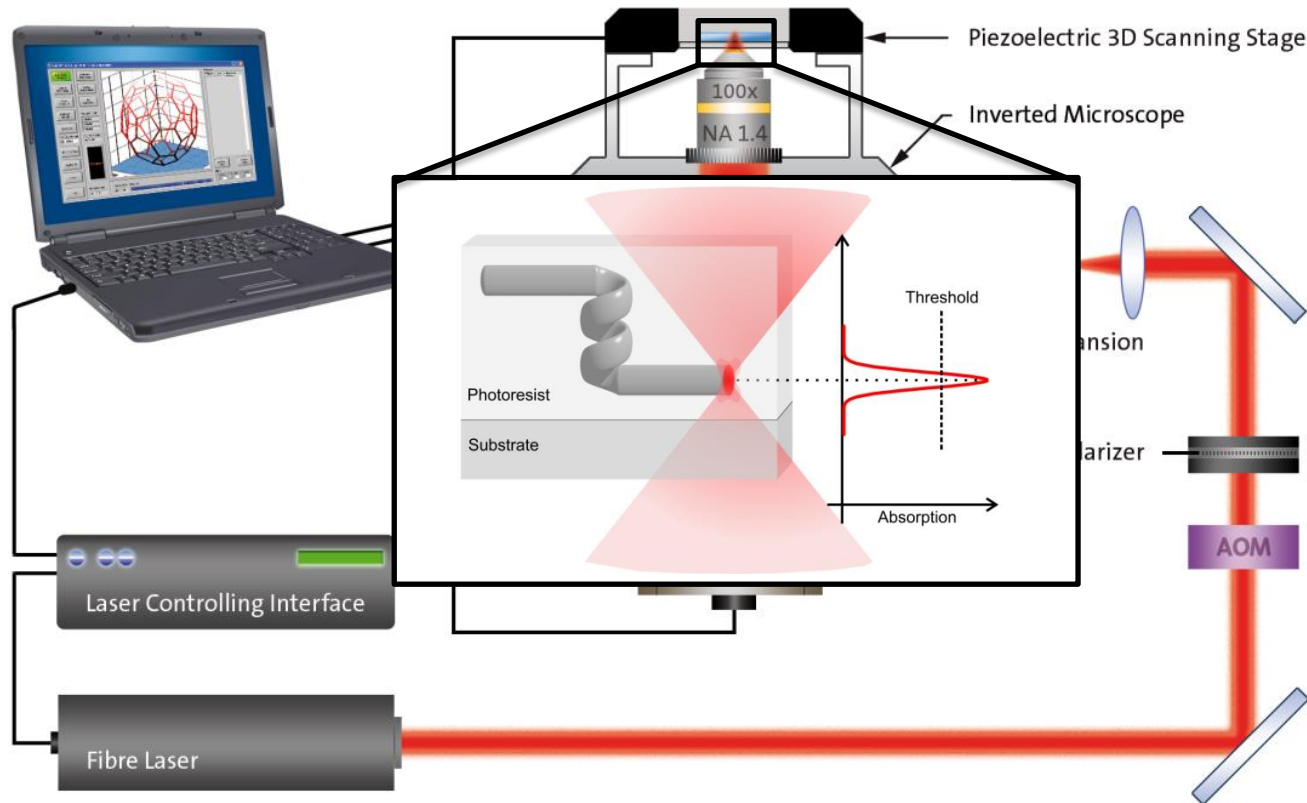


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 - Mechanical Metamaterials
- Summary



3D Printing by Direct Laser Writing



Light source for two-photon polymerization (TPP):

- Er-doped fiber laser @ $\lambda = 780 \text{ nm}$
- Pulse duration < 150 fs / repetition rate: 40-100 MHz
- Power > 45 mW

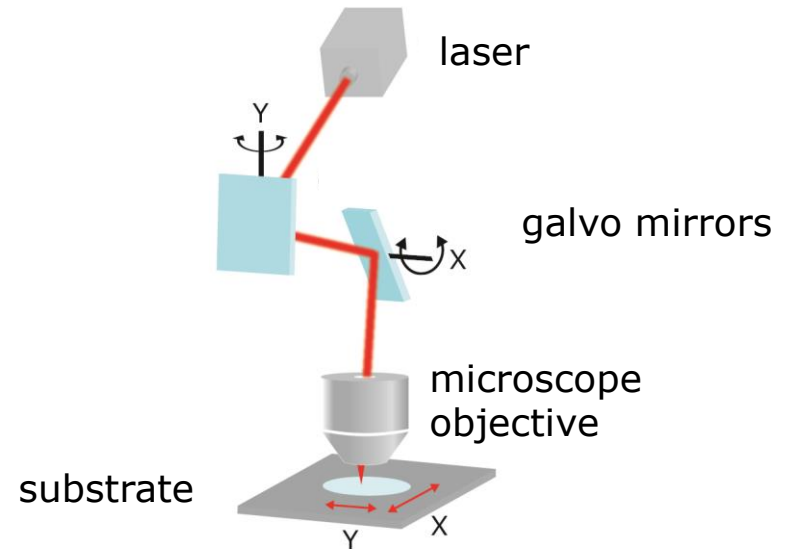
Embedded Writing Modes

Piezo mode



- Fixed laser focus, moving sample by piezoelectric stage
- 3-axes x-y-z-movement
- Arbitrary 3-dimensional trajectories
- Writing field up to $300 \times 300 \times 300 \mu\text{m}^3$
- PerfectShape®: Optimized speed to accuracy ratio

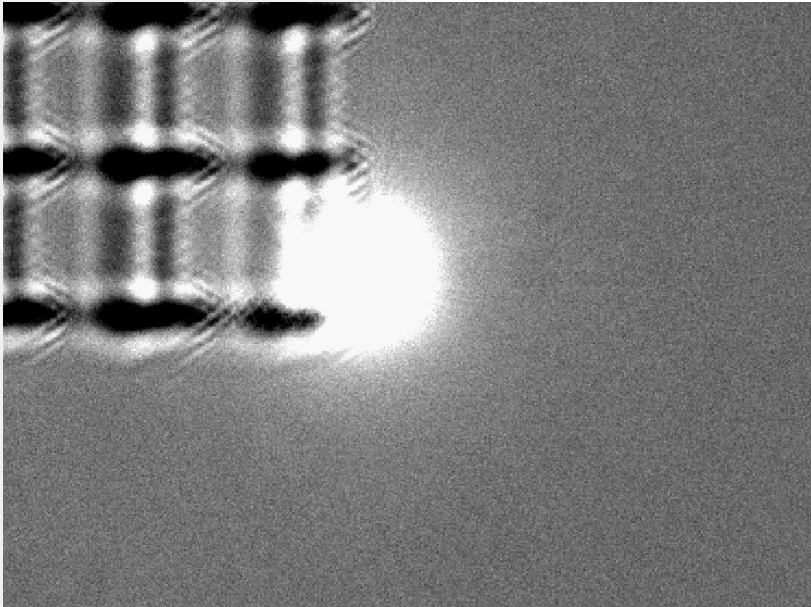
Galvo mode



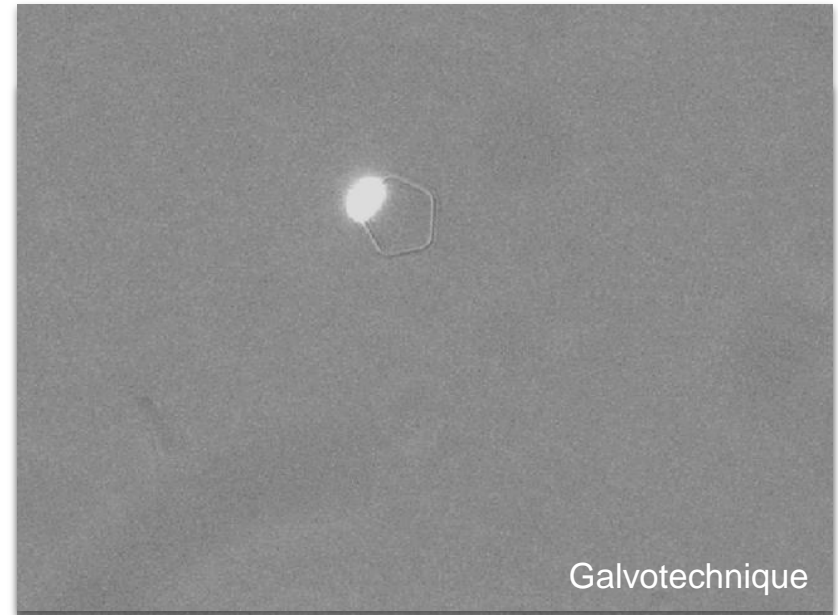
- Deflection of laser focus by galvo mirrors
- Lateral movement in x-y-plane
- Writing field depending on magnification of objective
- High-speed in-plane laser focus movement

Galvo- and Piezo-Scanning

Writing modes



Specs	Piezo Mode
Speed	Up to mm/s
Settling time	>100 ms
Scan rate	<10 lines/s
„Accuracy“	<10 nm
Volume	300 µm x 300 µm x 300 µm
Decription	True 3D scanning along 3D x-y-z trajectories Fixed beam, moving sample



Galvotechnique

Specs	Galvo Mode
Speed	Up to meters/s
Settling time	<1 ms
Scan rate	>100 lines/s
„Accuracy“	<10 µrad
Area	22 mm/Magnification
Description	Rapid x-y-scanning slice-by-slice Fixed sample, moving beam

Video of Printing Process



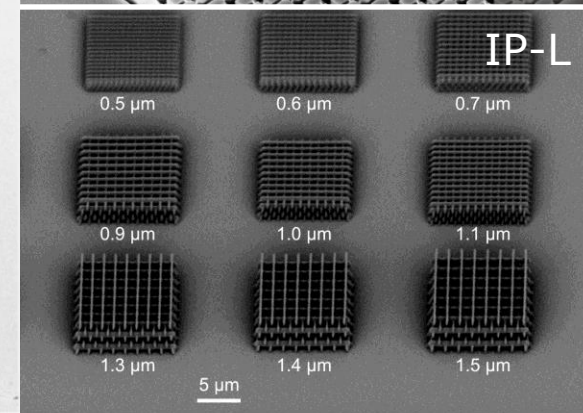
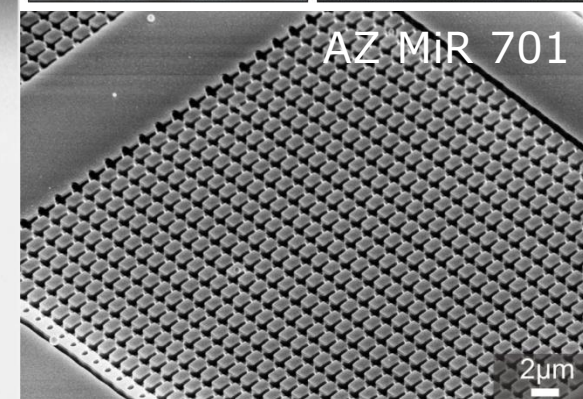
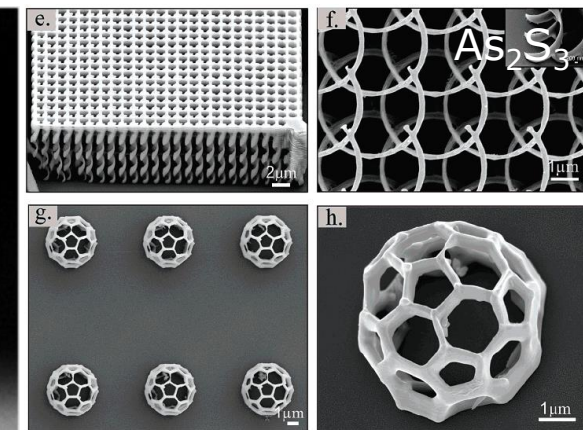
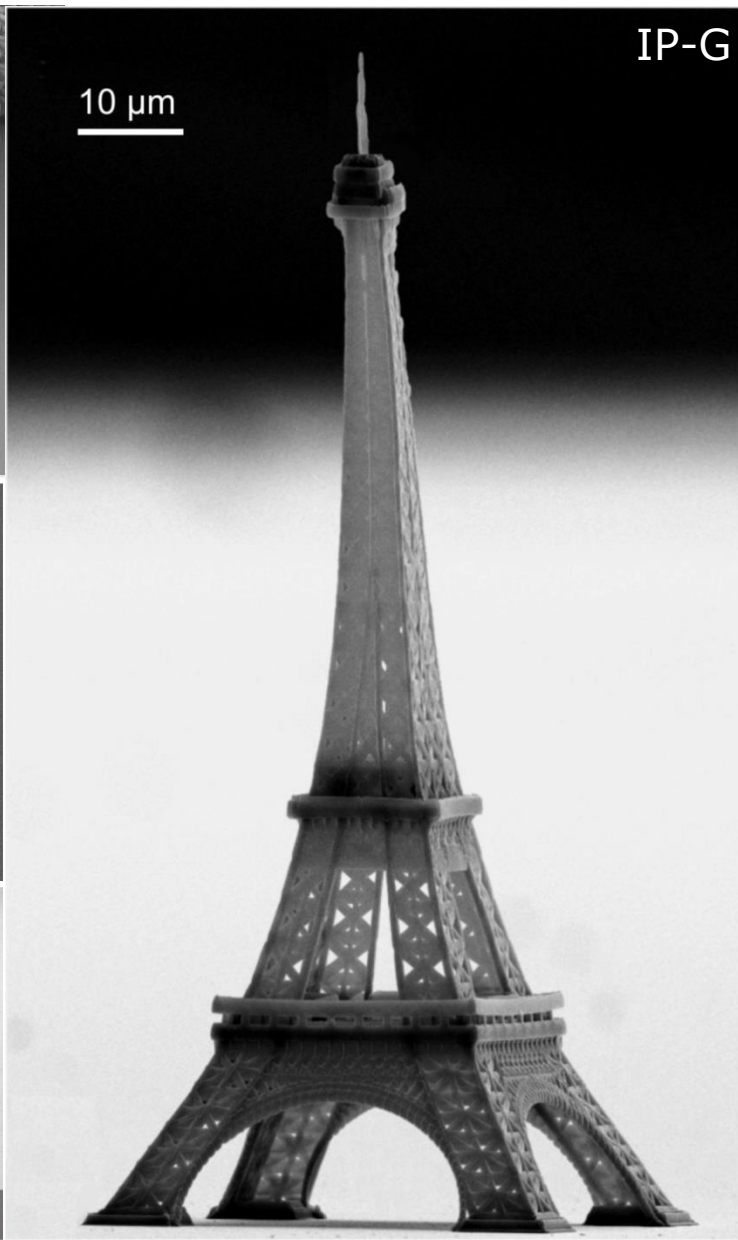
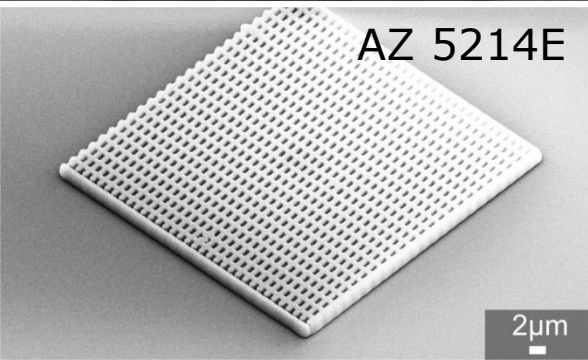
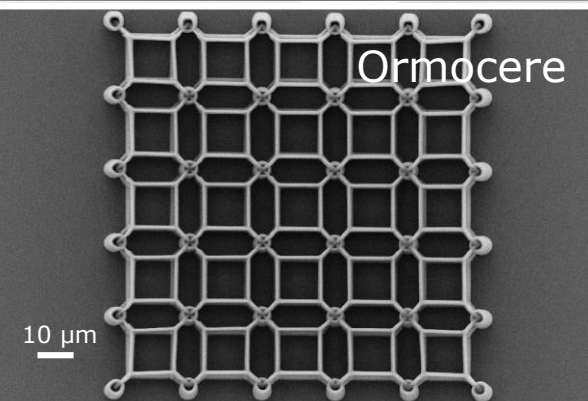
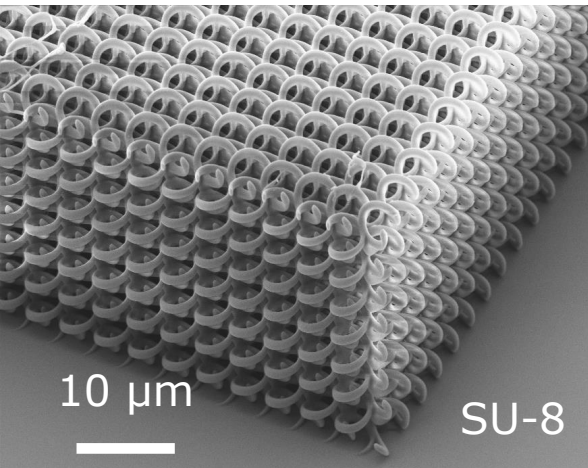
Application Video: 3D μ -Printing

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 - Micromechanics
- Company



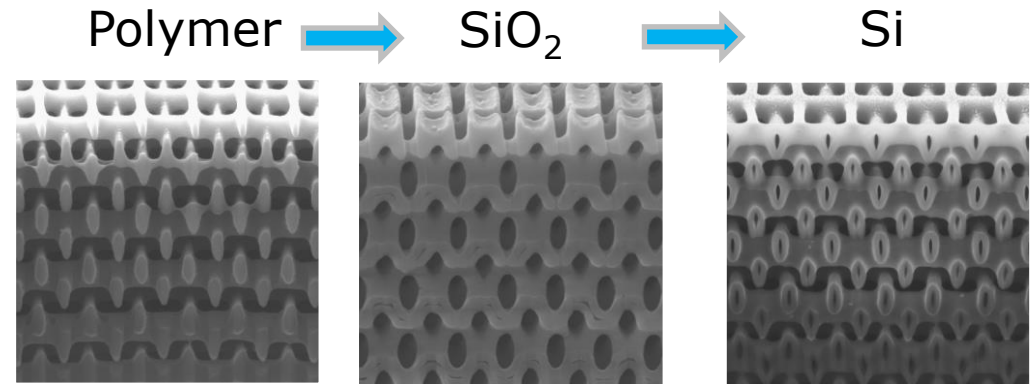
Materials – Printable Resins



Materials – Casting from Polymers

Dielectrics:

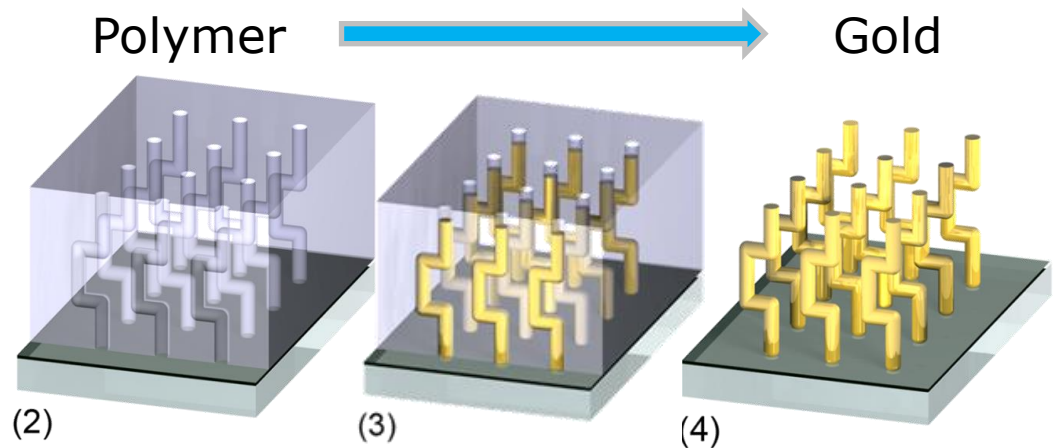
- Silicon Chemical Vapor Deposition (CVD)
- Silica Pulsed Layer Deposition (PLD)
- Titania Atomic Layer Deposition (ALD)



M. Hermatschweiler *et al.*, Adv. Funct. Mater. **17**, 2273 (2007)

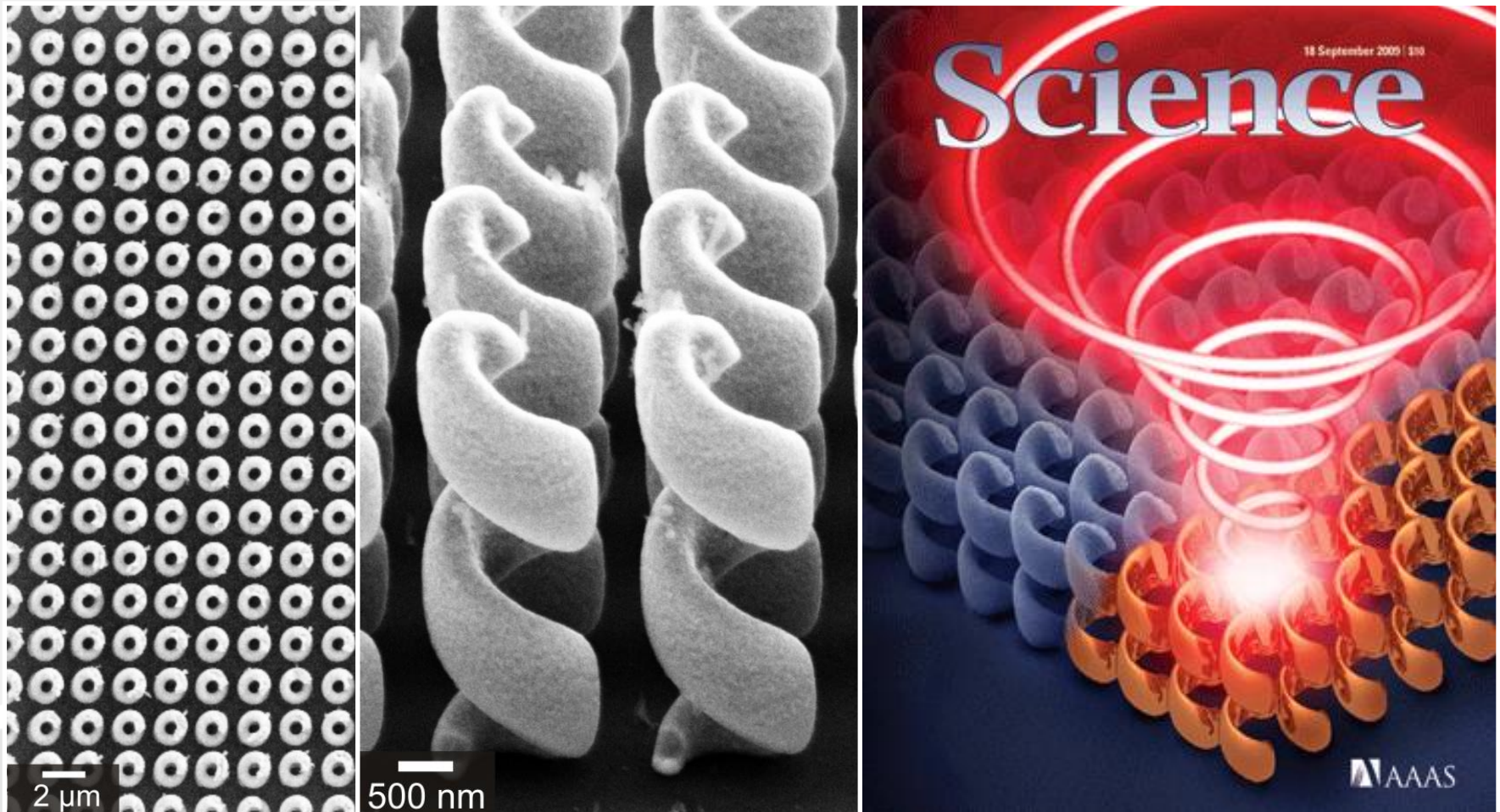
Metals:

- Gold Electroplating / Galvanization
- Silver Chemical Vapor Deposition (CVD)



J. Gansel *et al.*, Science **325**, 1513 (2009)

Casting of Metal (Gold)



J. Gansel et al., Science **325**, 1513 (2009)

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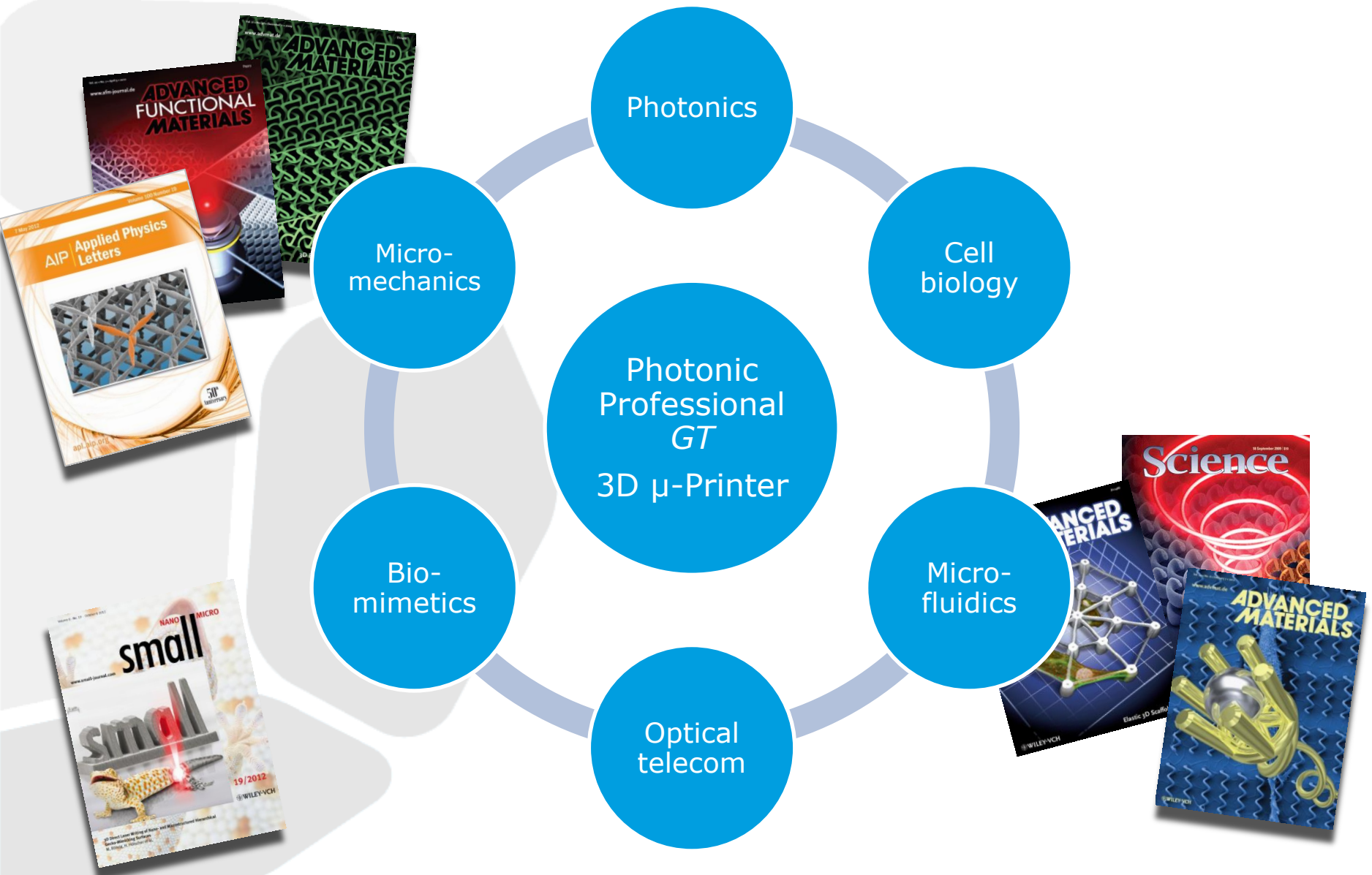


Source and permission: Kurt Wirz, Basel, CH

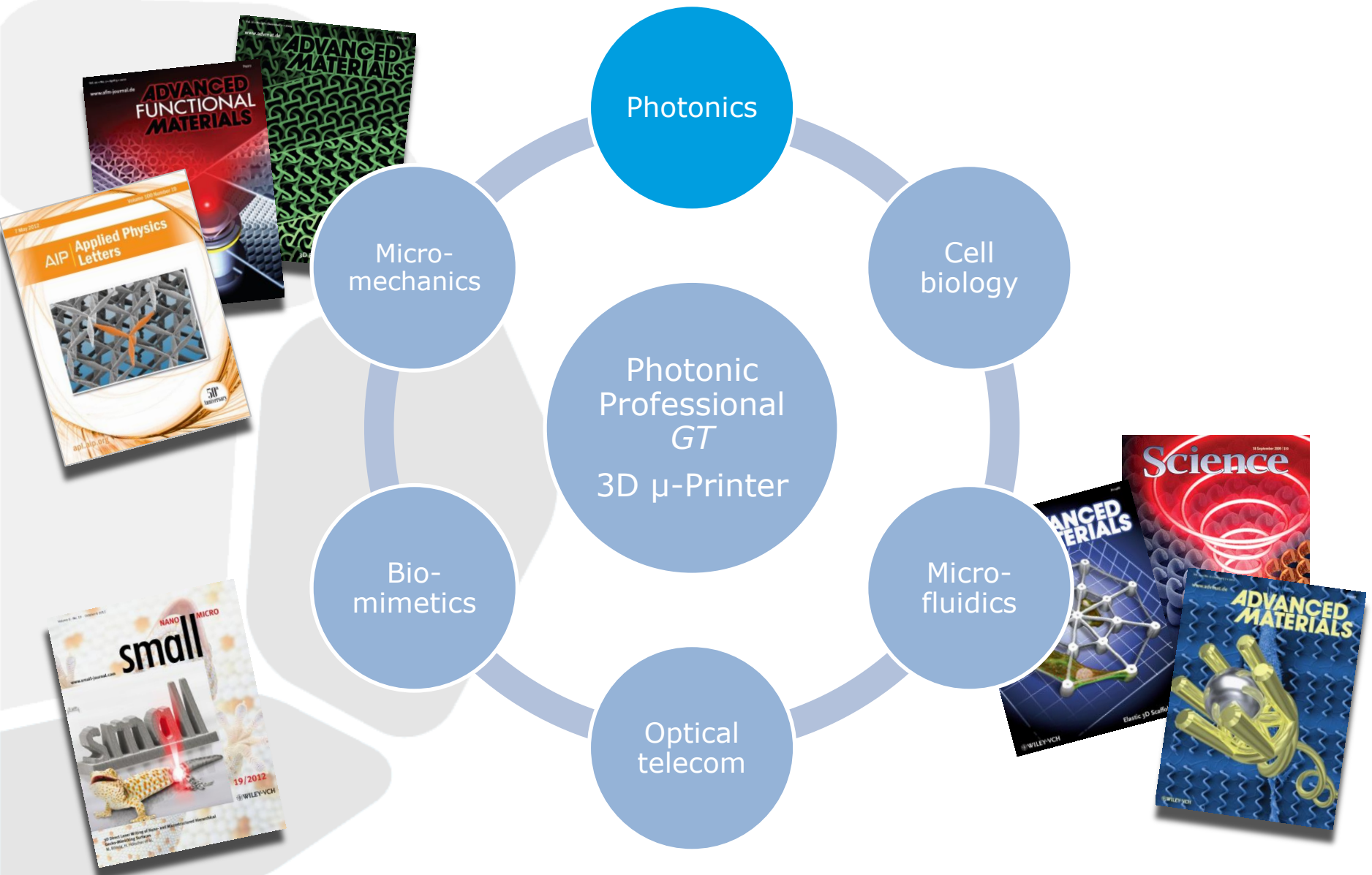


Source: <http://www.nanoqed.org/2009.php>

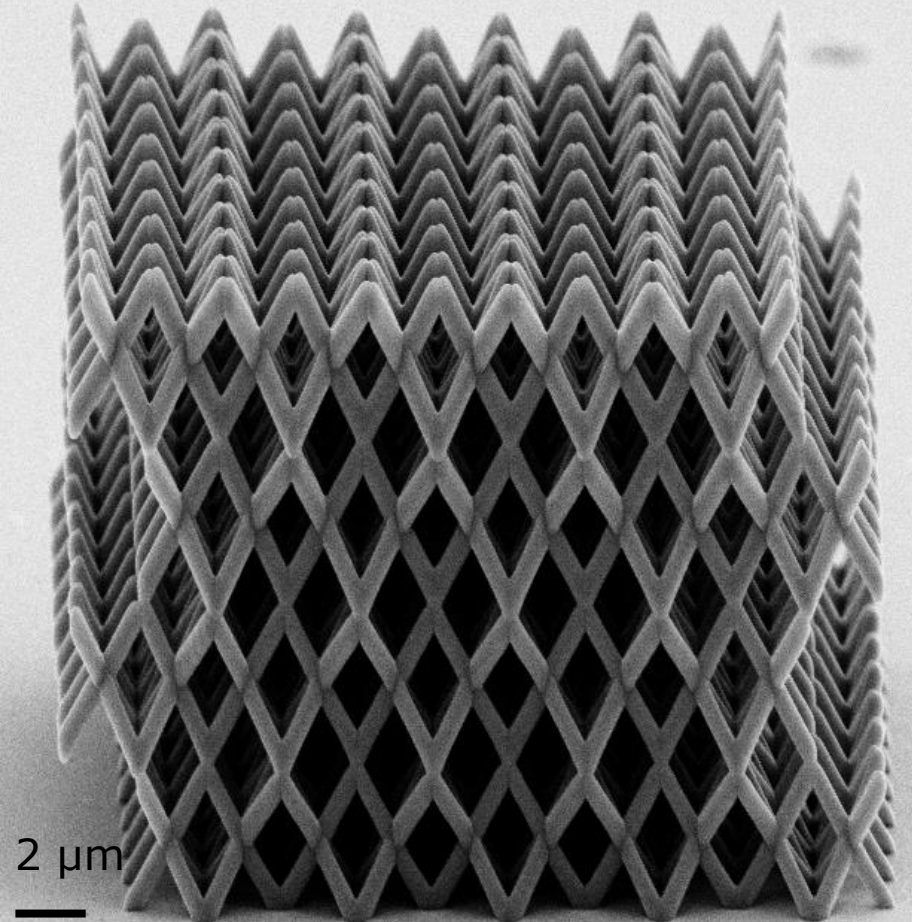
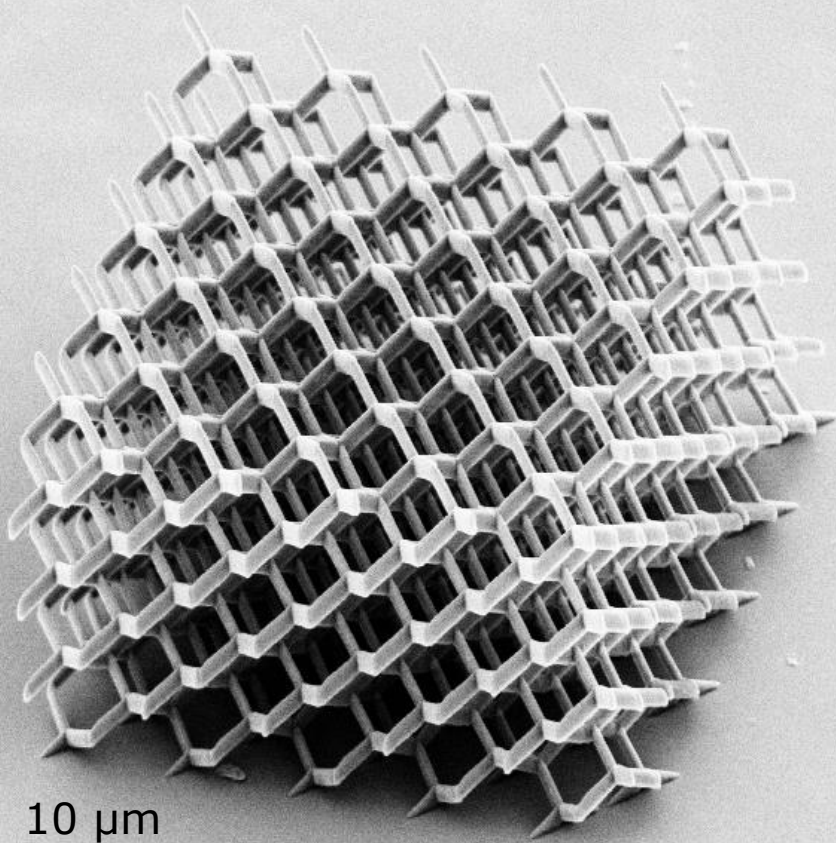
Applications



Applications



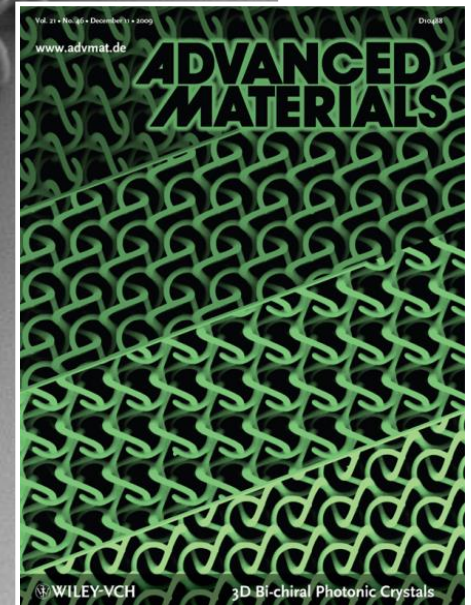
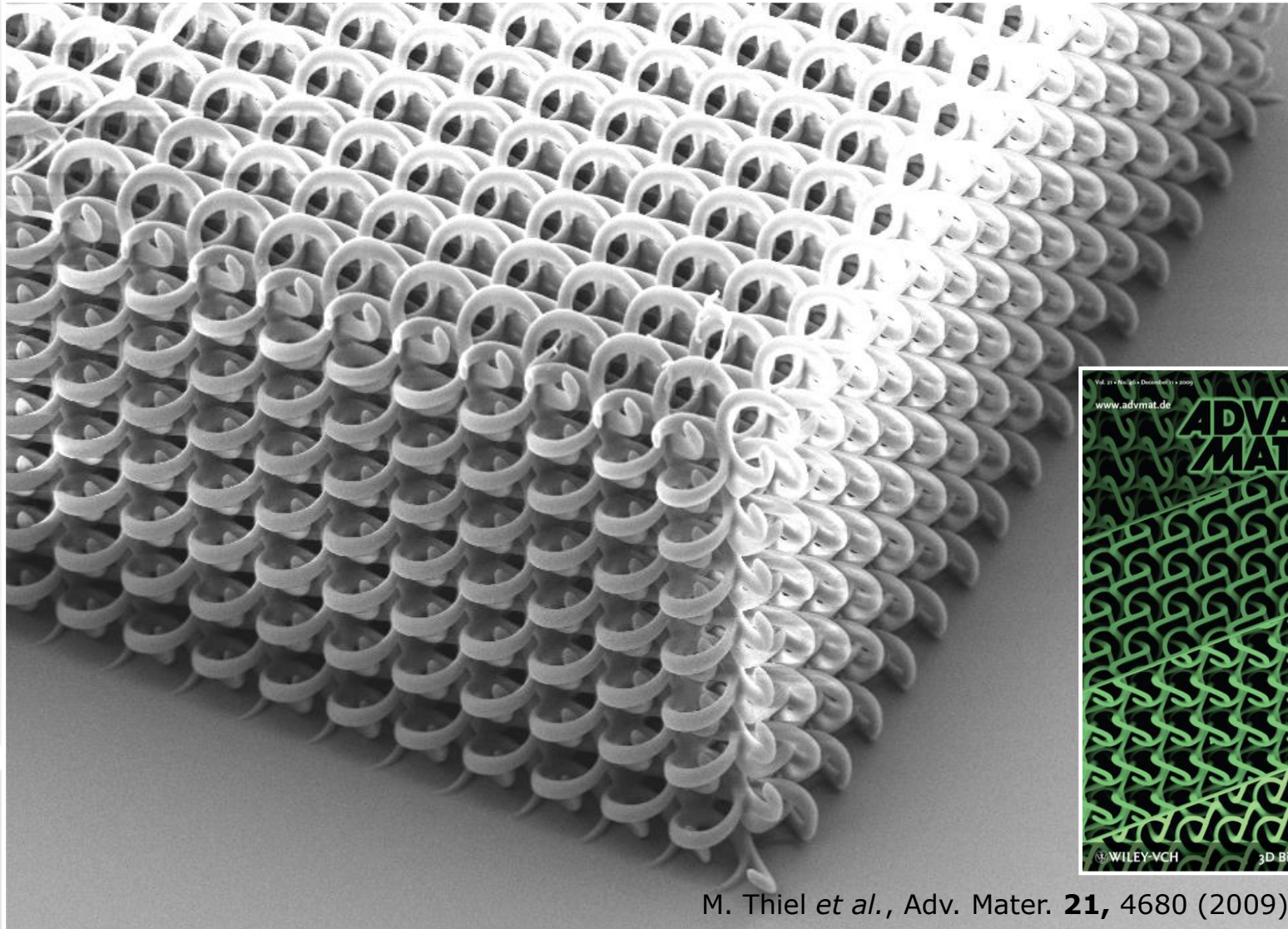
3D Photonic Crystals



according to K. Edagawa *et al.*, PRL 100, 013901 (2008)

Design provided by ITMO, Russia

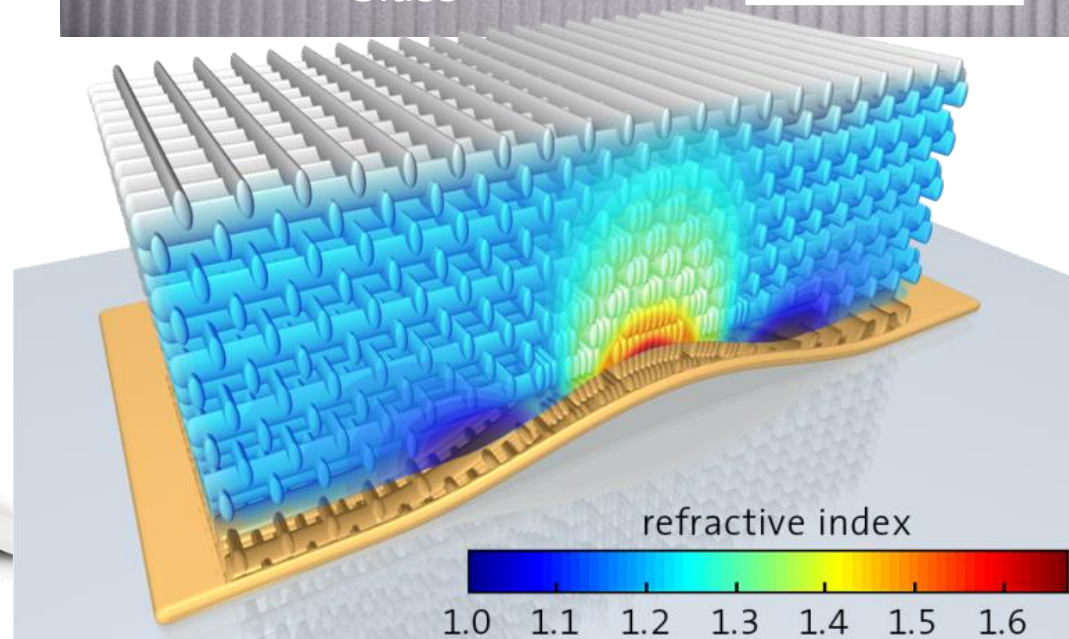
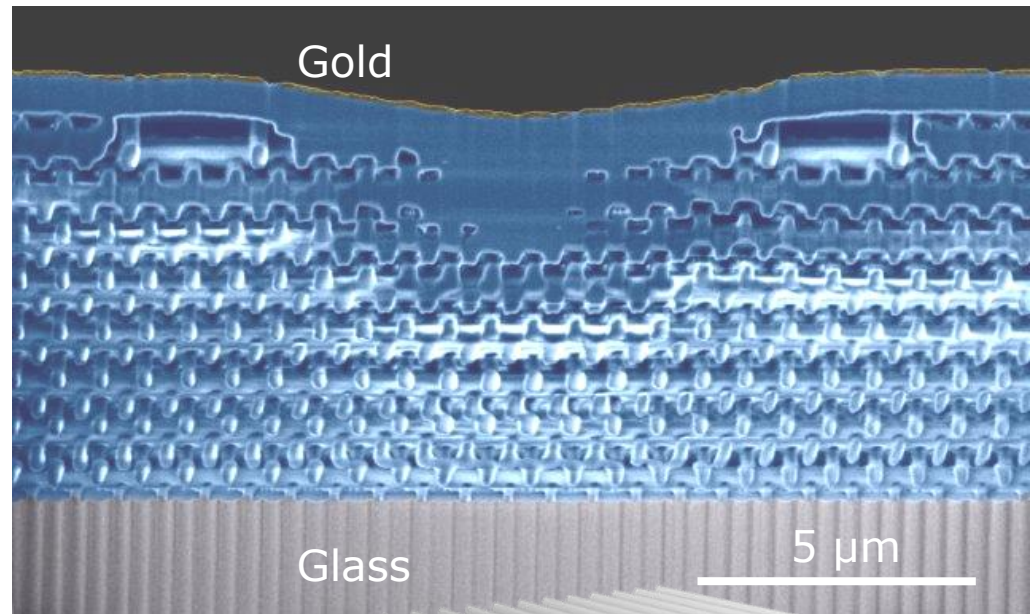
3D Photonic Crystals



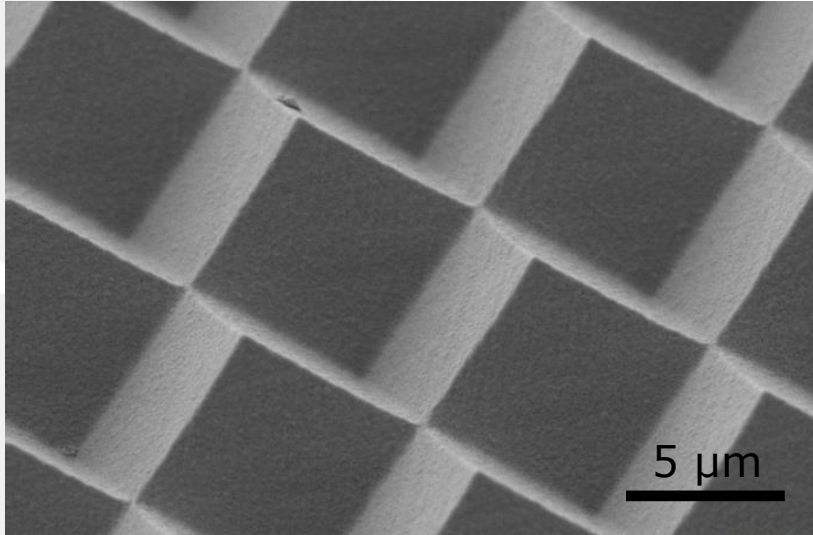
M. Thiel *et al.*, Adv. Mater. **21**, 4680 (2009)

3D Photonics: Cloaking

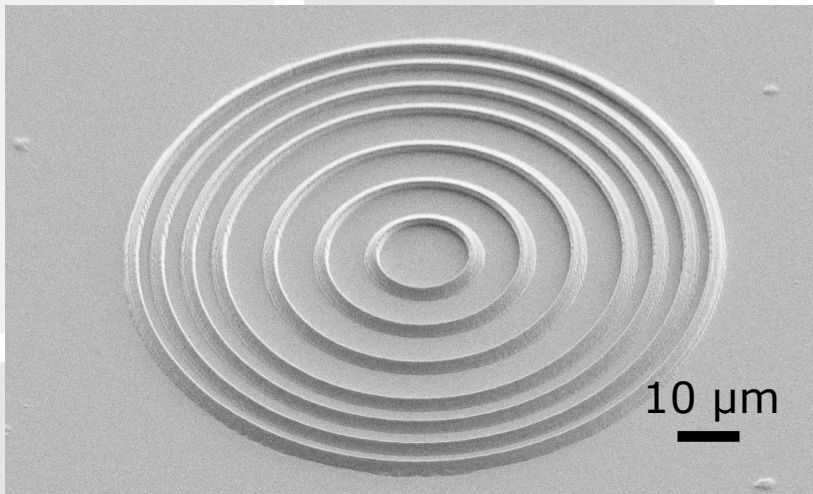
T. Ergin *et al.*,
Science **328**, 337 (2010)



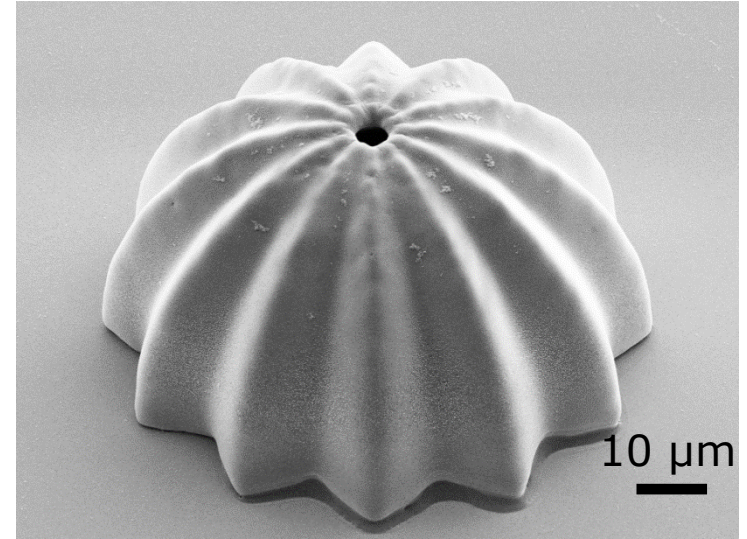
Micro-Optics



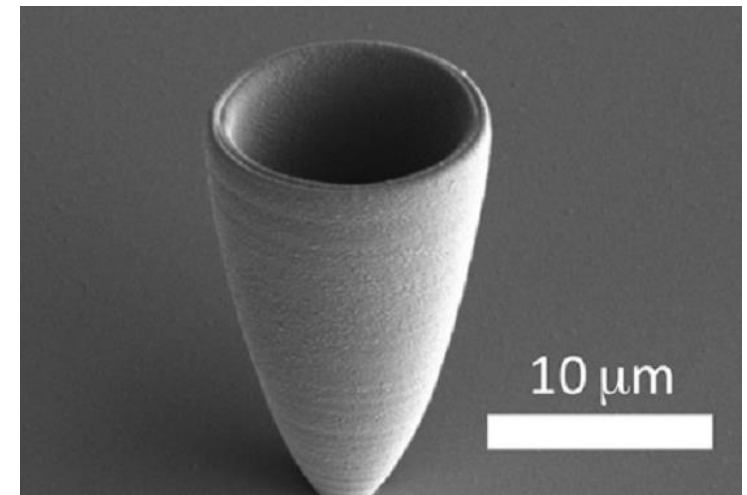
Retroreflector



Fresnel Zone Plate



P. Schmaelzle, PARC, Design APL 45, 2572 (2006)

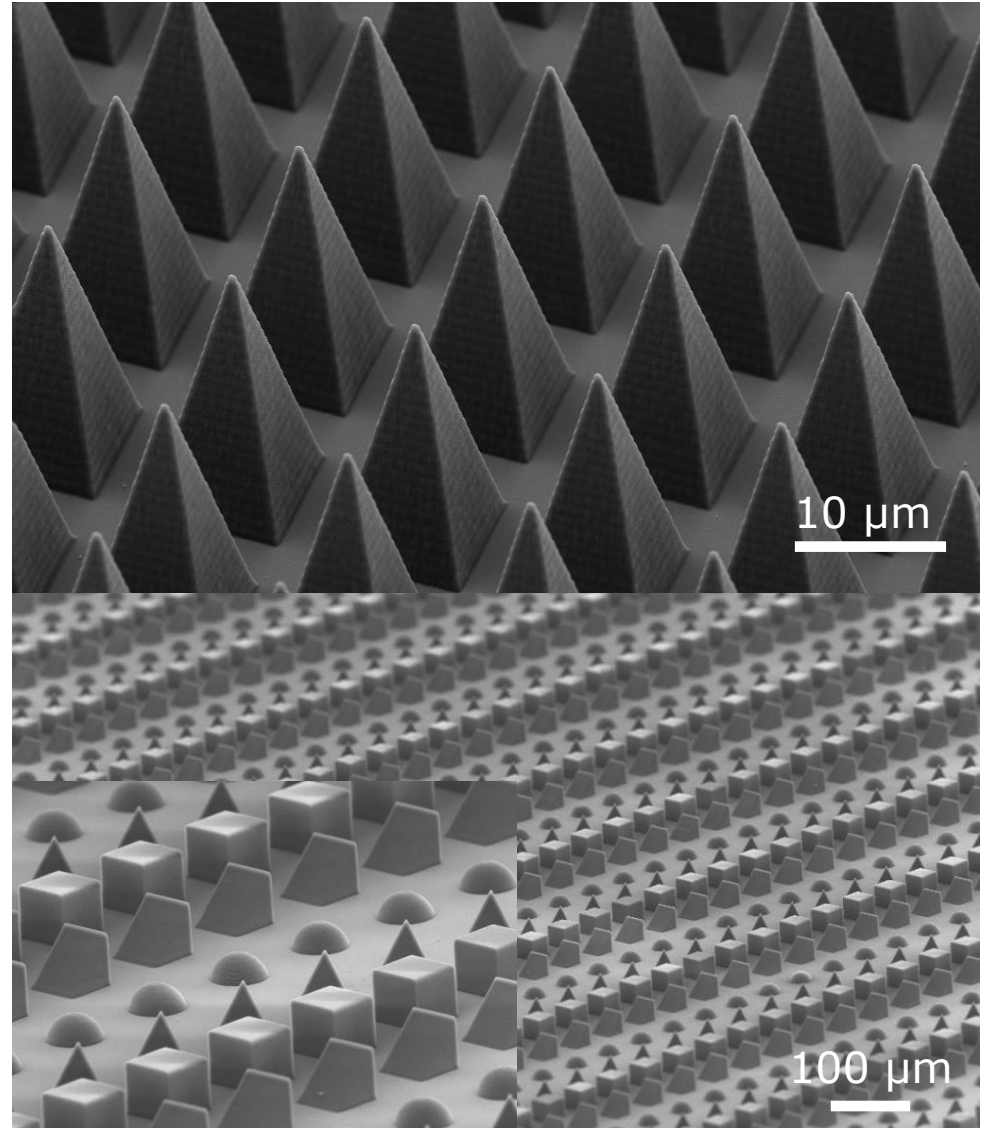


J. H. Atwater et al., APL 99, 151113 (2011)

TPP Advantages to Gray Scale Litho

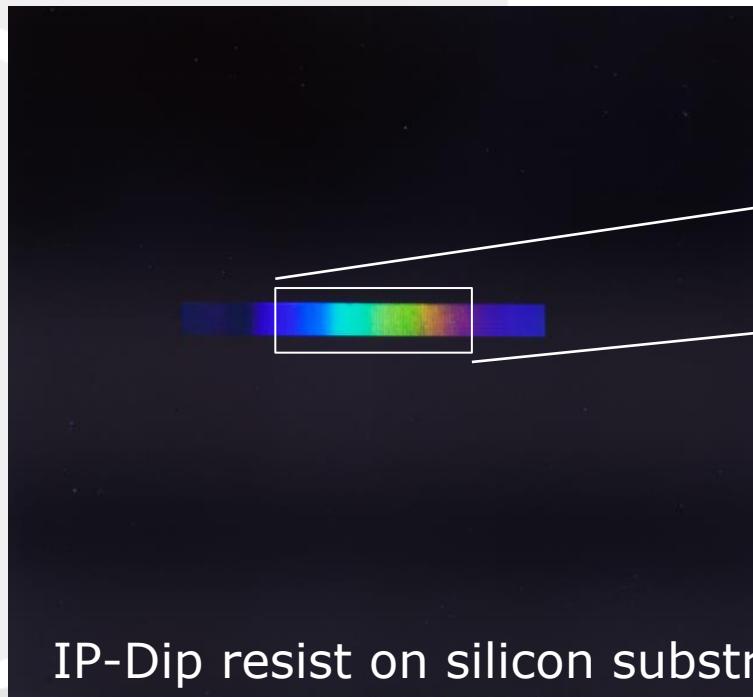
- **High reproducibility:**
 - Negative tone resists (TPP) are very forgiving to fluctuating ambient conditions (temperature, humidity, development time, soft bake, post exposure bake etc.)
 - this is not the case for positive tone resists which are necessary for gray scale lithography when using opaque substrates
- **Height easily tunable:**
 - height independent of resist thickness
 - DiLL (Dip-in Laser Lithography) allows for highest reproducibility and quality independent of structural height
 - different heights on same wafer easy to realize
- **Slender process chain for liquid resists (solvent-free!):**
 - No spin-coating
 - No thickness control necessary
 - No soft bake
 - No post exposure bake
- **Visual feedback:**

The writing process can directly be observed for multiple photoresists
- **Structural design:**
 - No intelligence needed taking into account Beer's law
 - what you design is what you get
- **Undercuts** are possible and potentially could also be used for lift-off

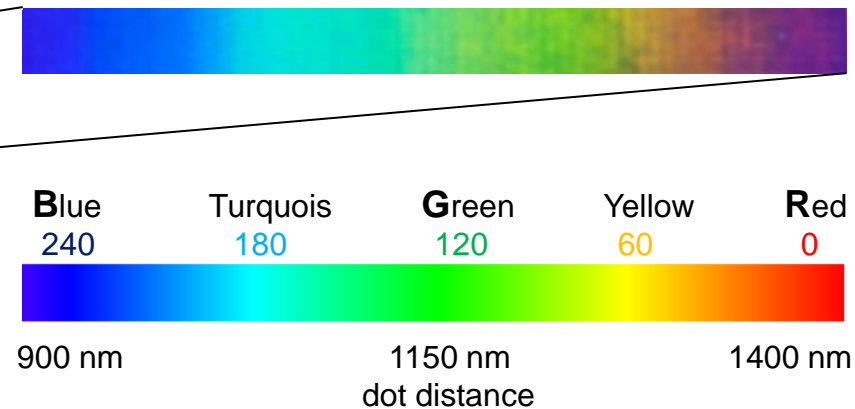


Photonic Colors / Security Labels

Color mapping - 10 mm x 1 mm rainbow



We use the *hue* of HSV color model



exposure time = 0.05 ms, settling time = 0.5 ms; 40x, NA=1.3, 50 μ m x 50 μ m field size, 201 dot array pixel with periods of 600 nm to 1600 nm (5nm increment)

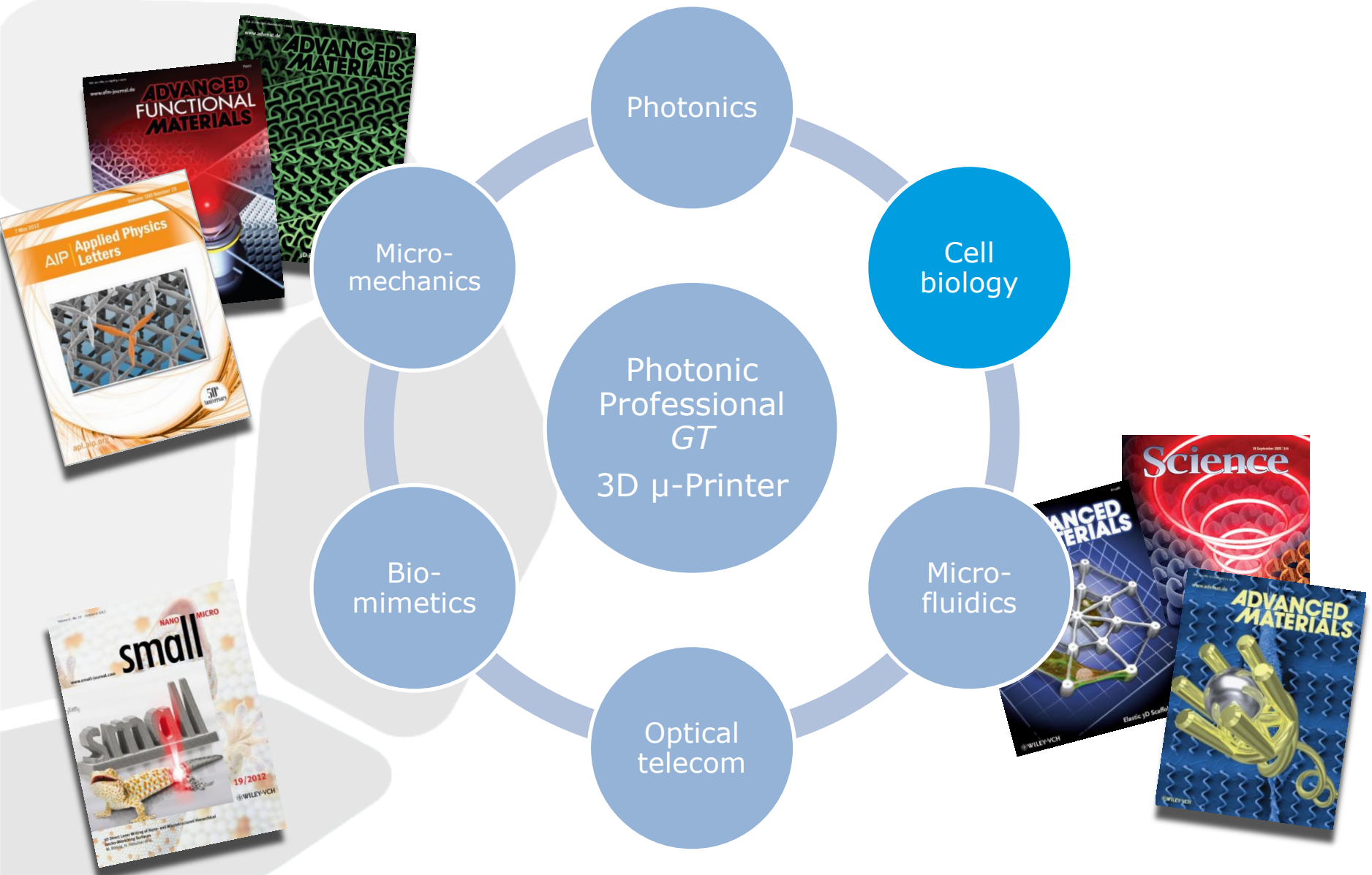
Photonic Colors / Security Labels

Graphical Input (png, jpg,...)

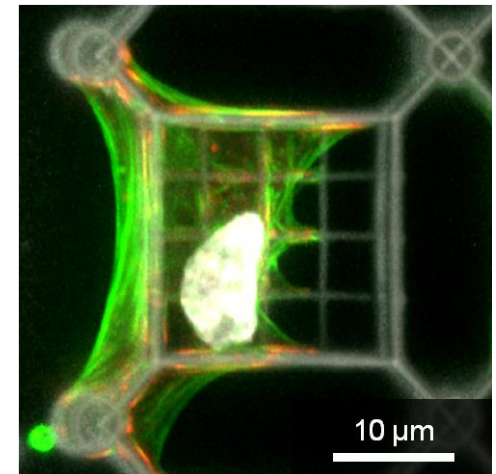
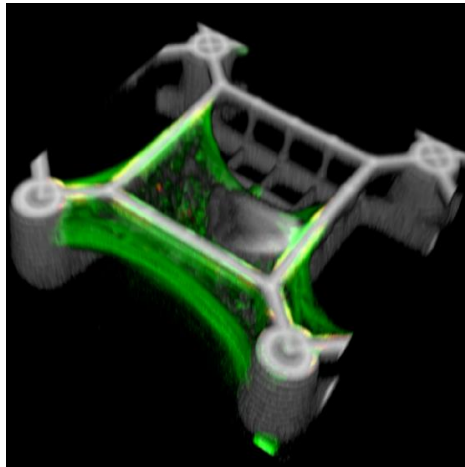
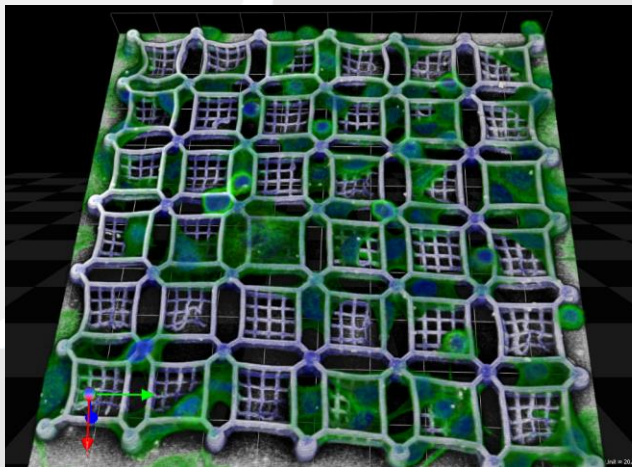
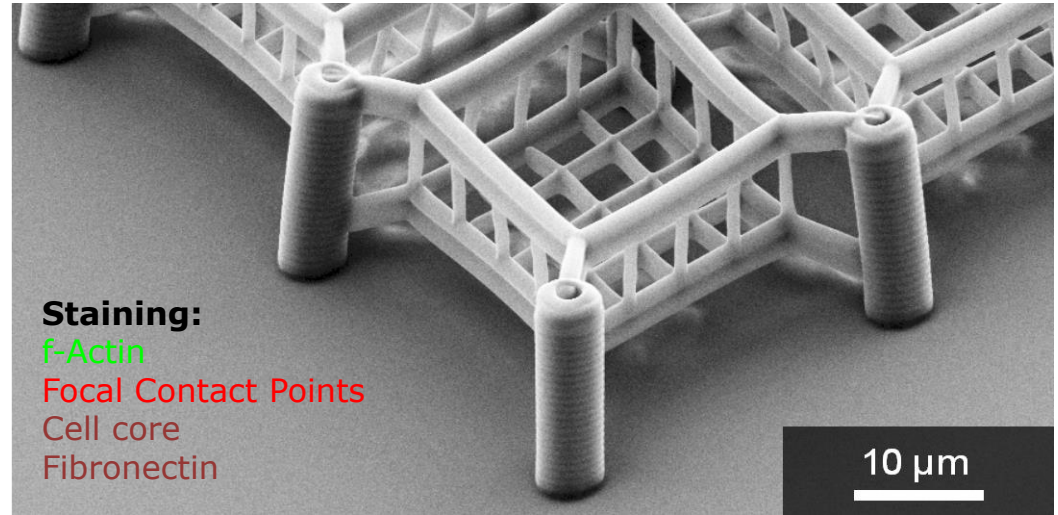
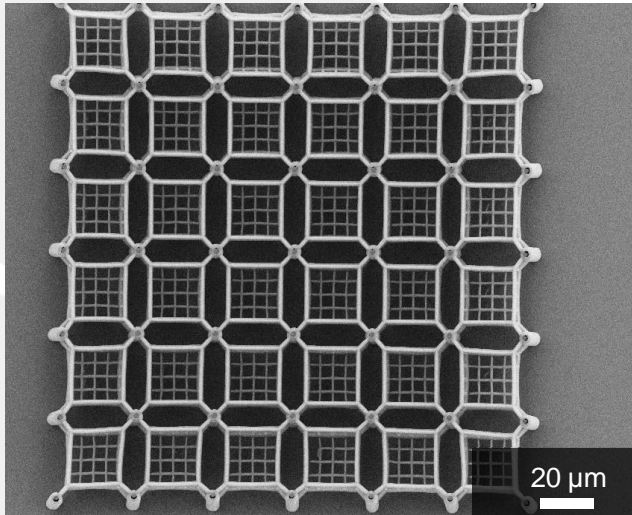


exposure time = 0.05 ms, settling time = 0.5 ms; 40x, NA=1.3, 50 μ m x 50 μ m field size, 201 dot array pixel with periods of 600 nm to 1600 nm (5nm increment)

Applications



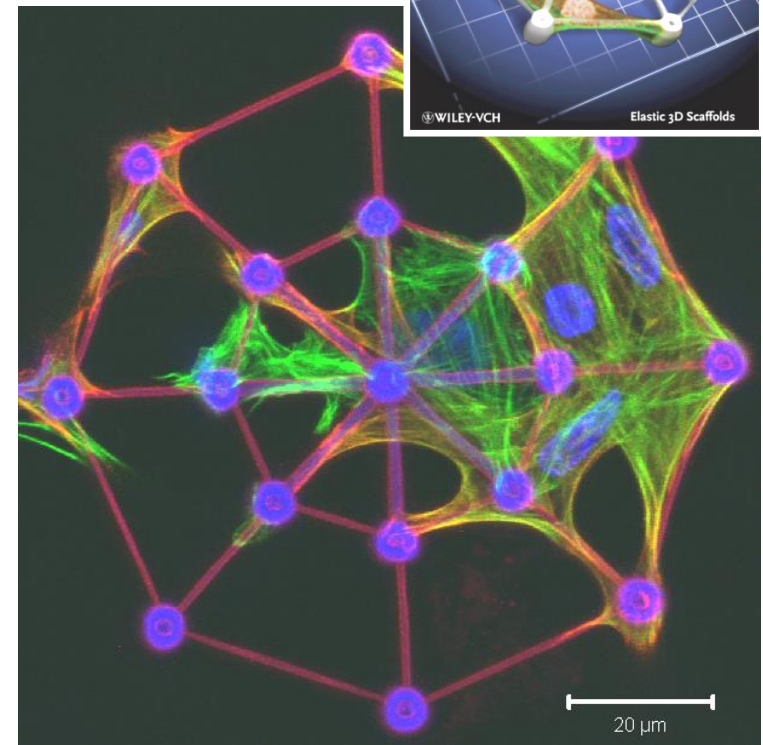
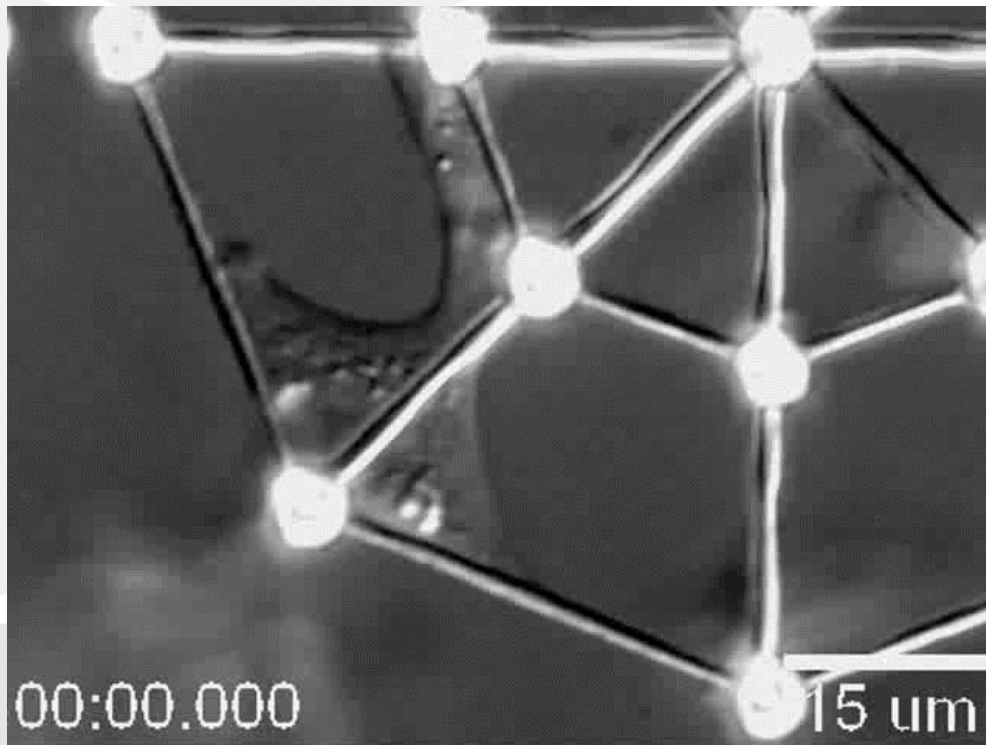
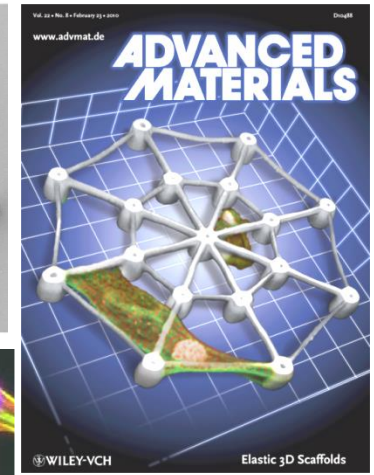
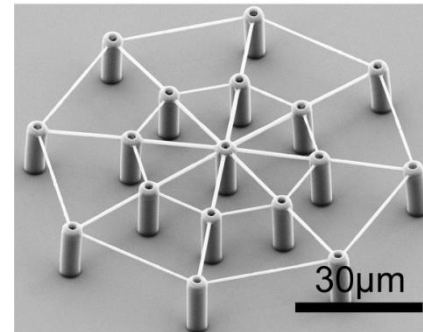
Fabricated Structures & Cell Culture



A Gym for Cells

- Primary culture of chicken heart cells

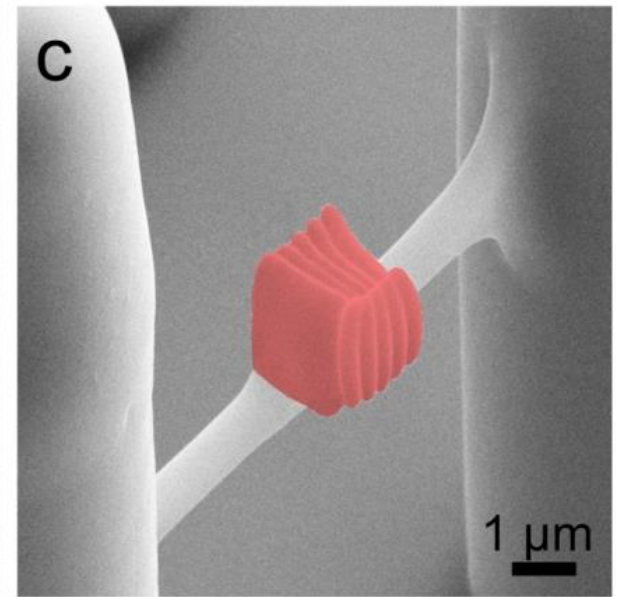
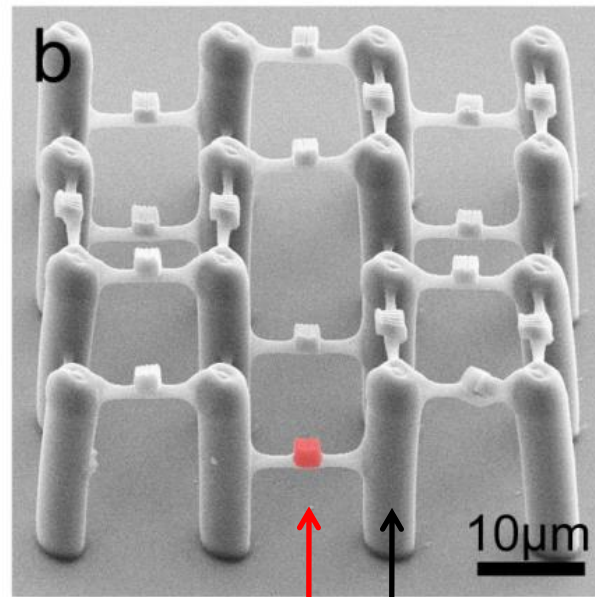
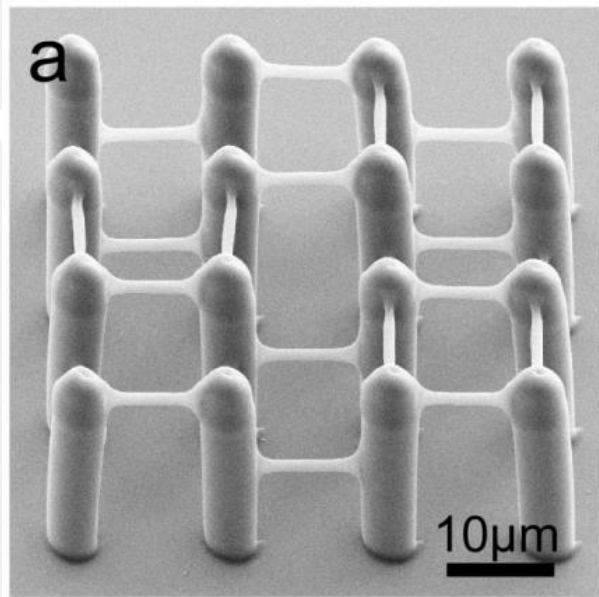
F. Klein *et al.*, Adv. Mater. **22**, 868 (2010)



Multiple Exposure – Realignment to Markers



nanoscribe



Protein repellant
Protein binding

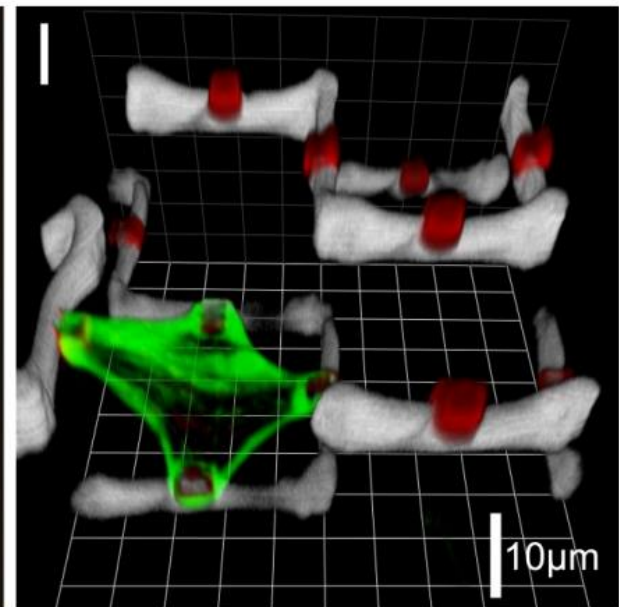
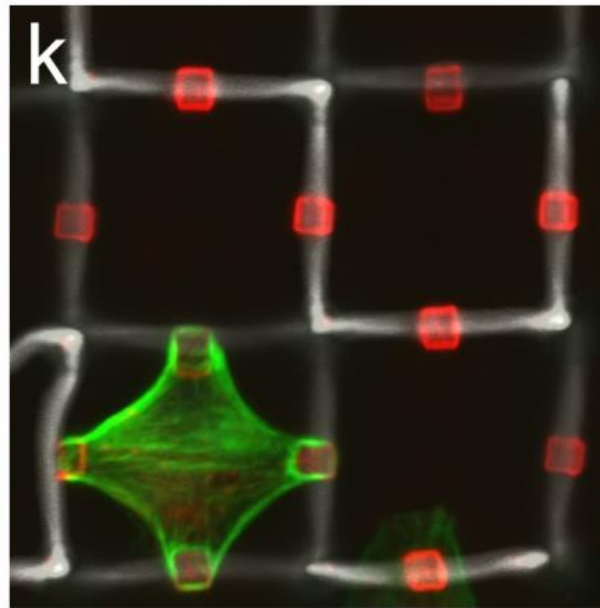
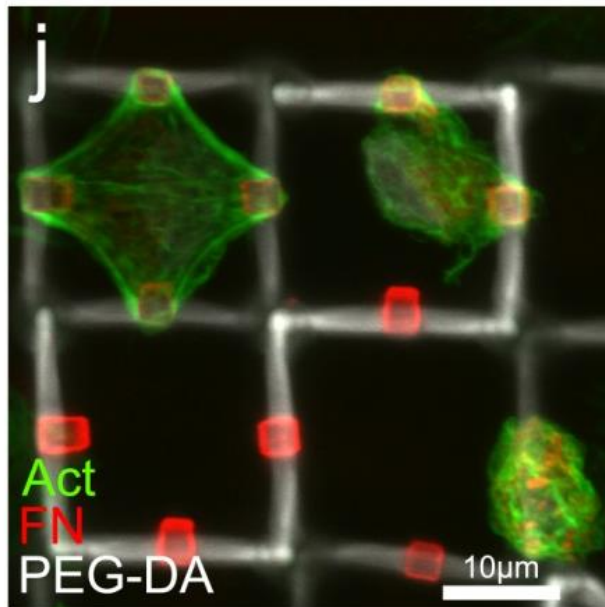
PEG-DA/PETA
ORMOCERE

F. Klein & B. Richter *et al.*, Adv. Mater. 23, 1341-1345 (2011)

Multiple Exposure – Realignment to Markers

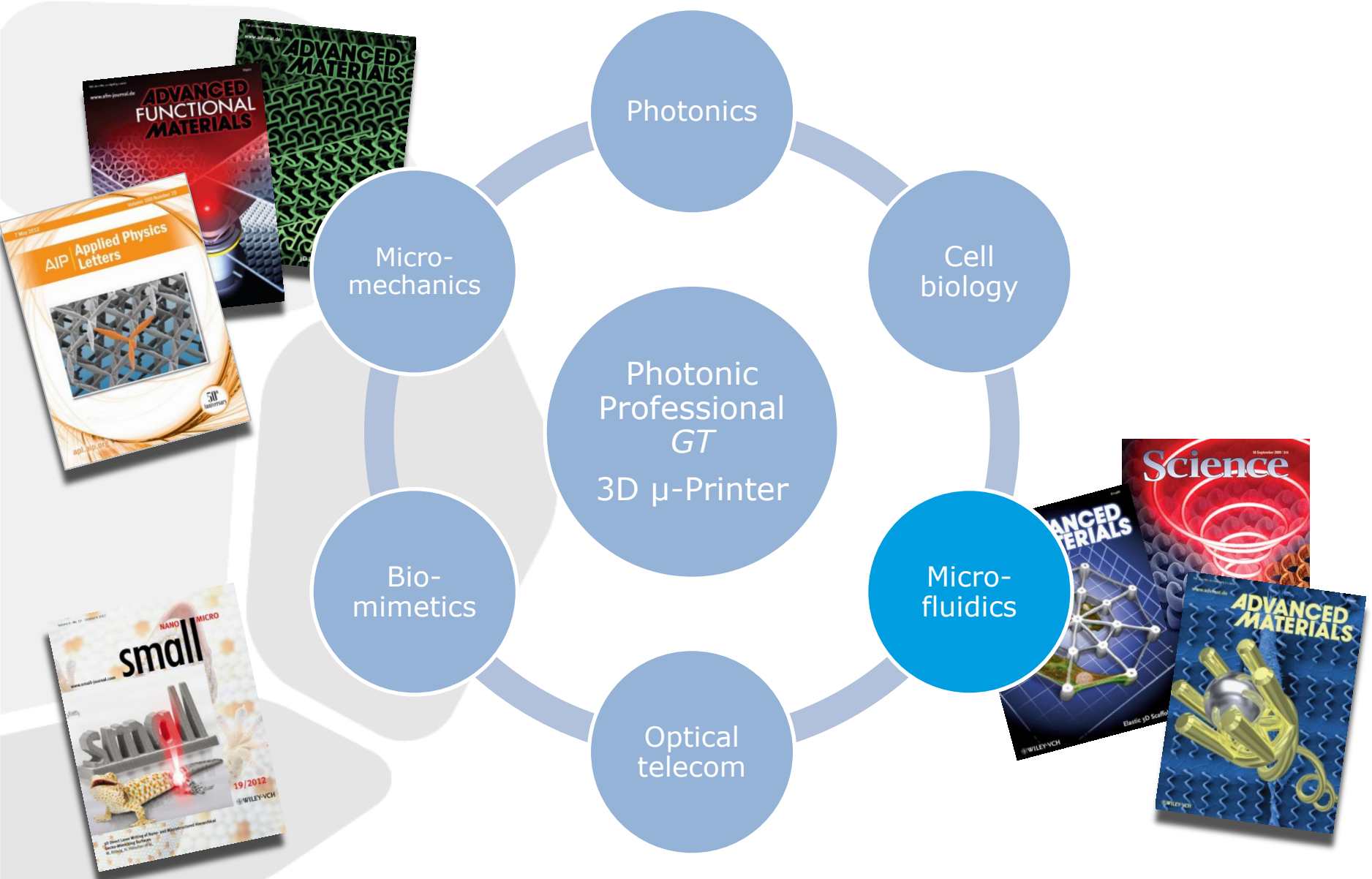


nanoscribe

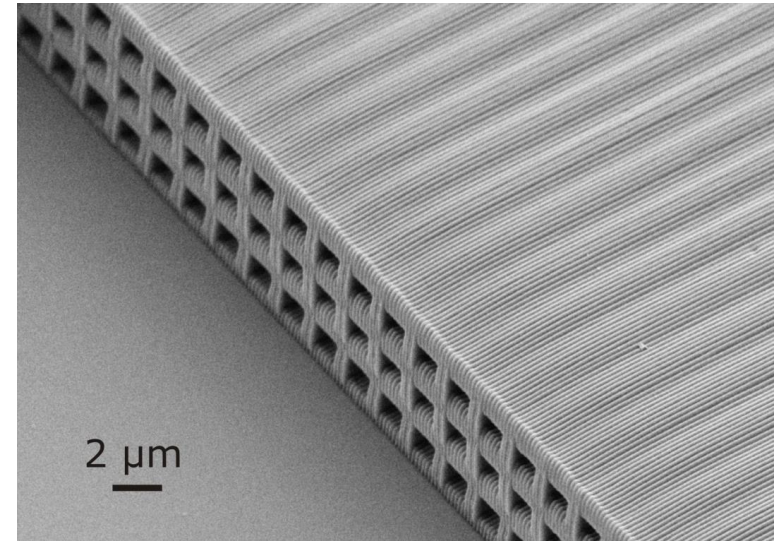
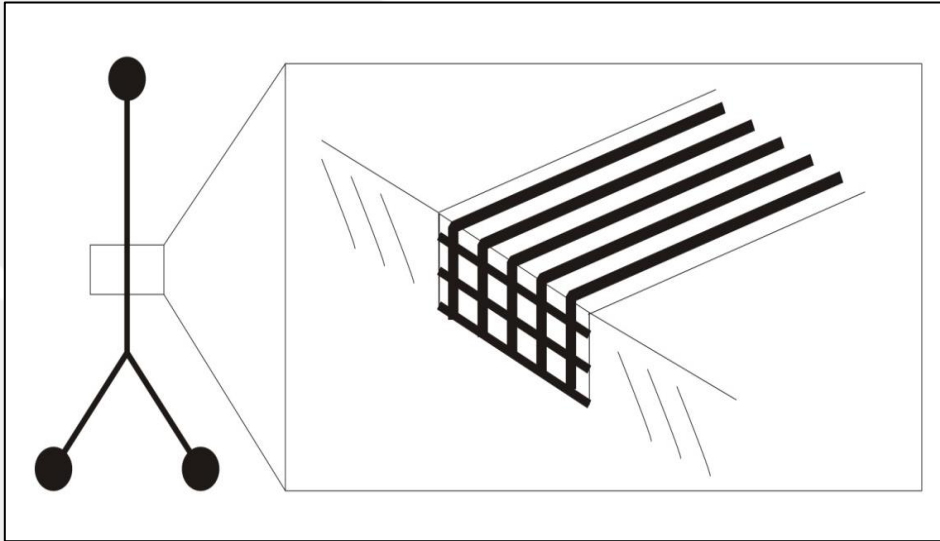


F. Klein & B. Richter *et al.*, Adv. Mater. 23, 1341-1345 (2011)

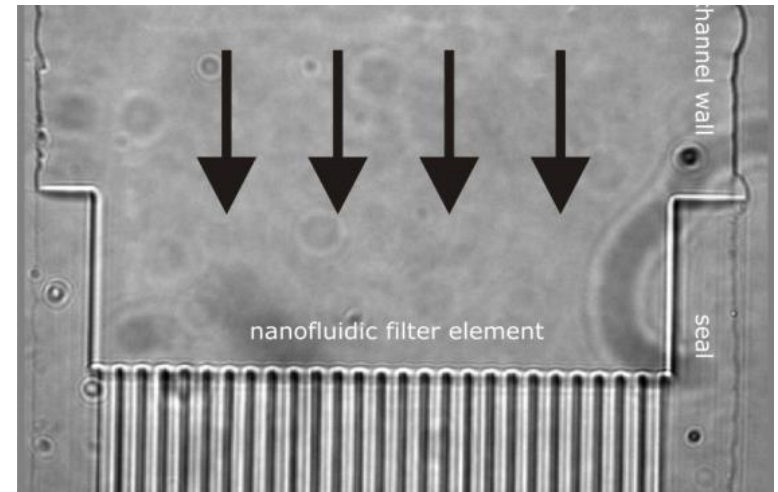
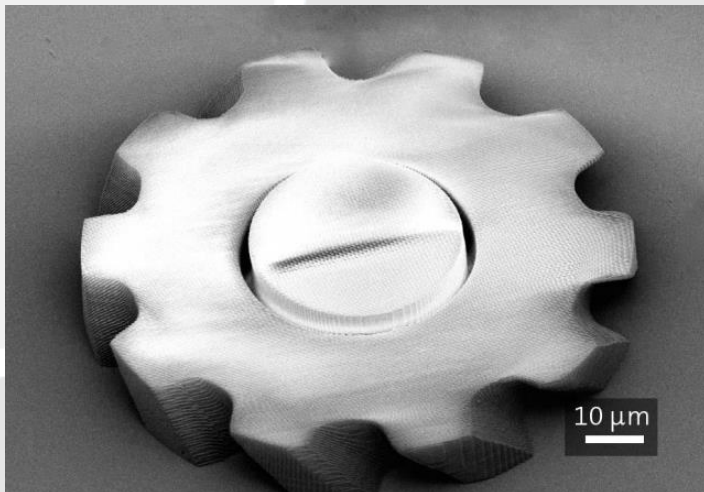
Applications



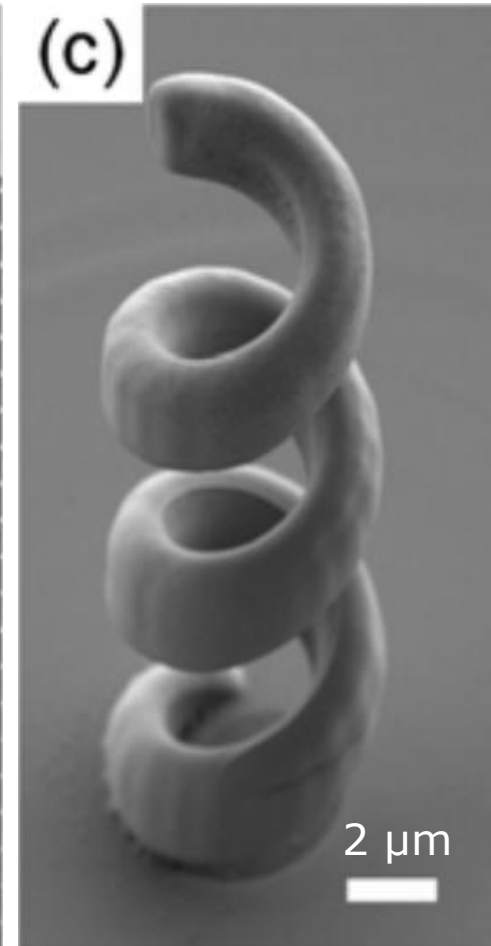
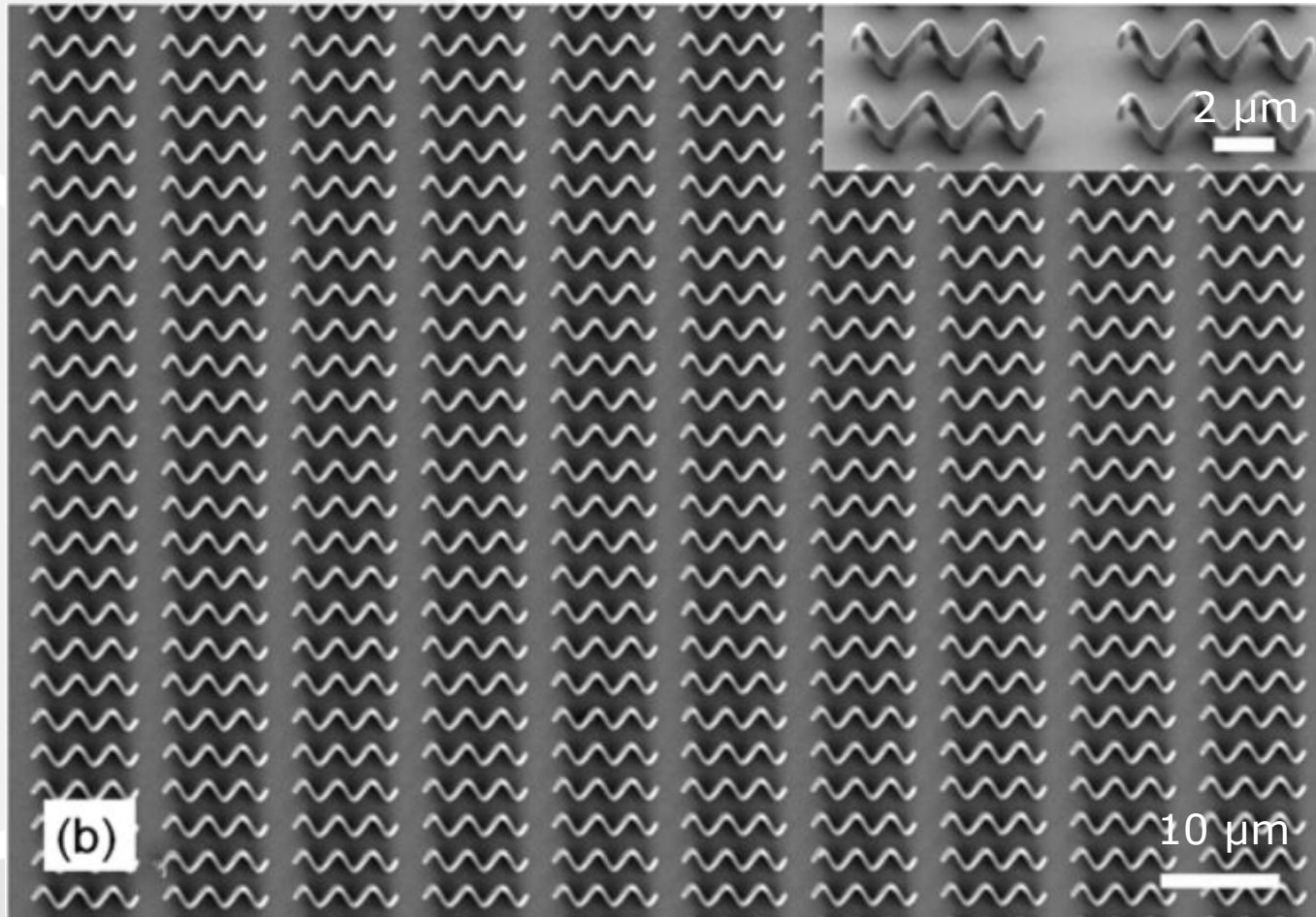
Writing of Microfluidic Elements



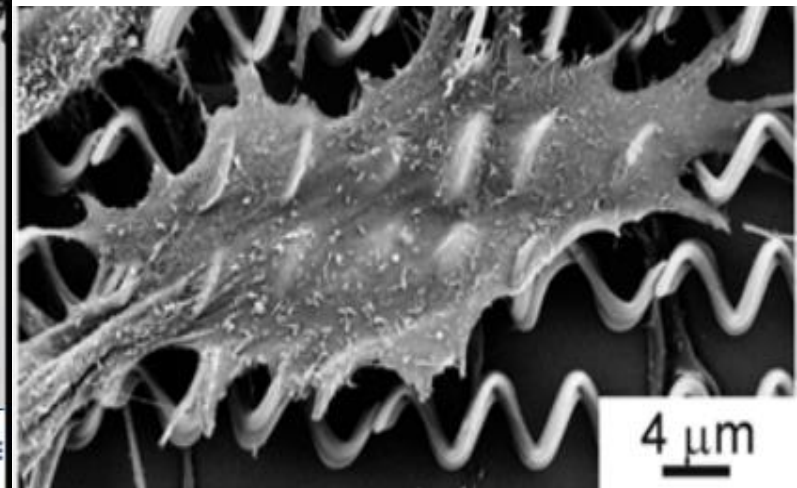
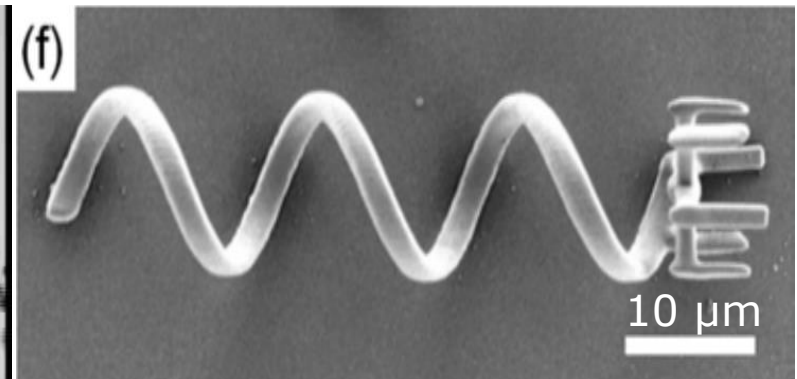
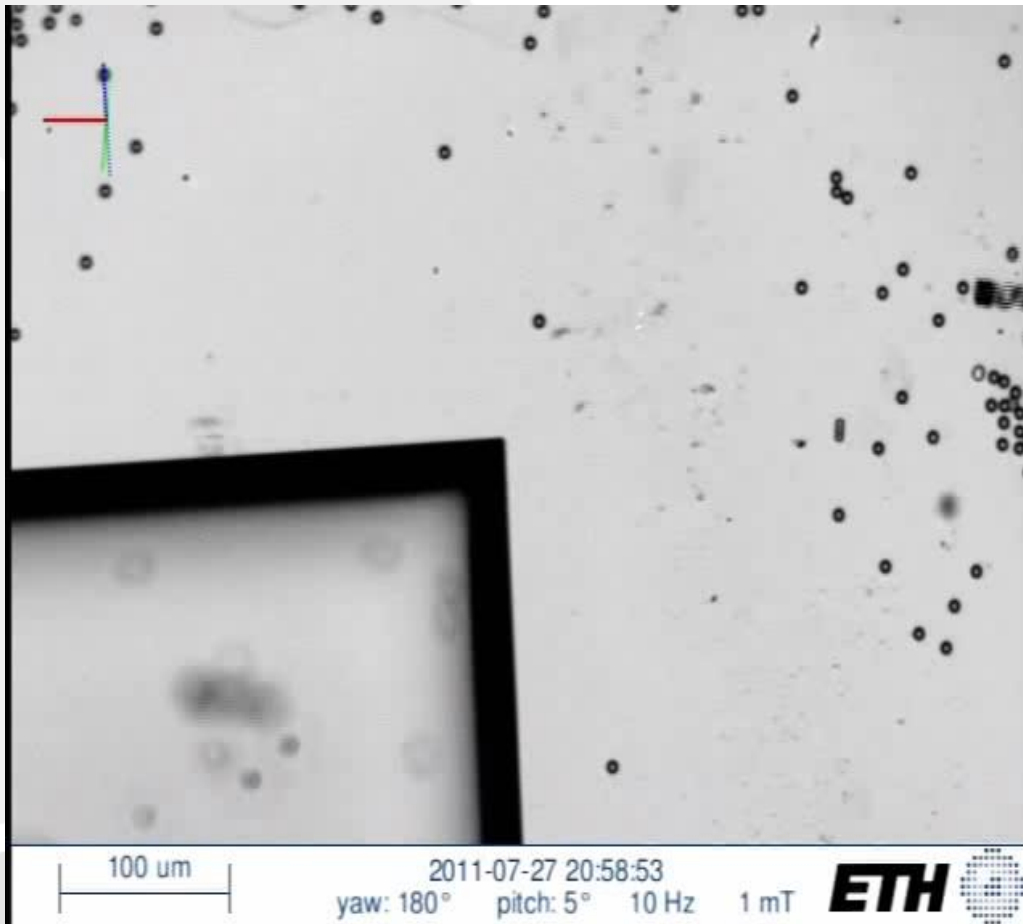
Design by A.-M. Haghiri-Gosnet, LPN-CNRS, France



Magnetic Helical Micromachines



Magnetic Helical Micromachines



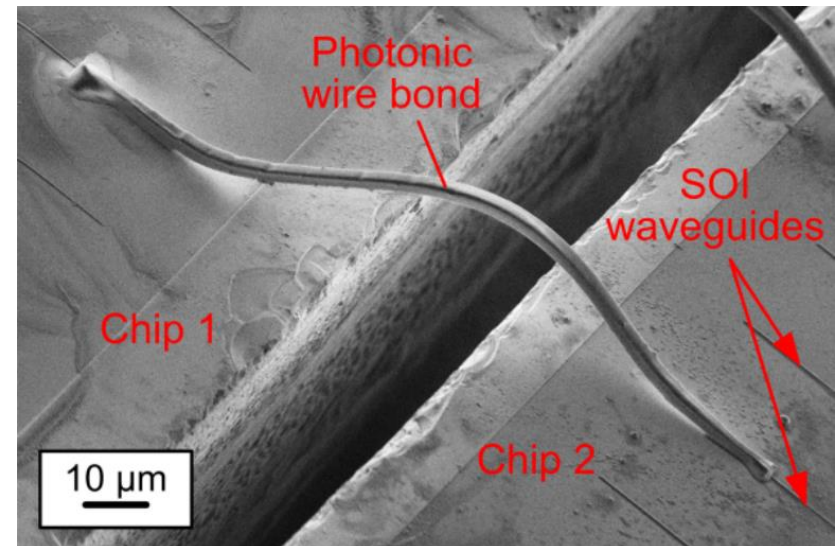
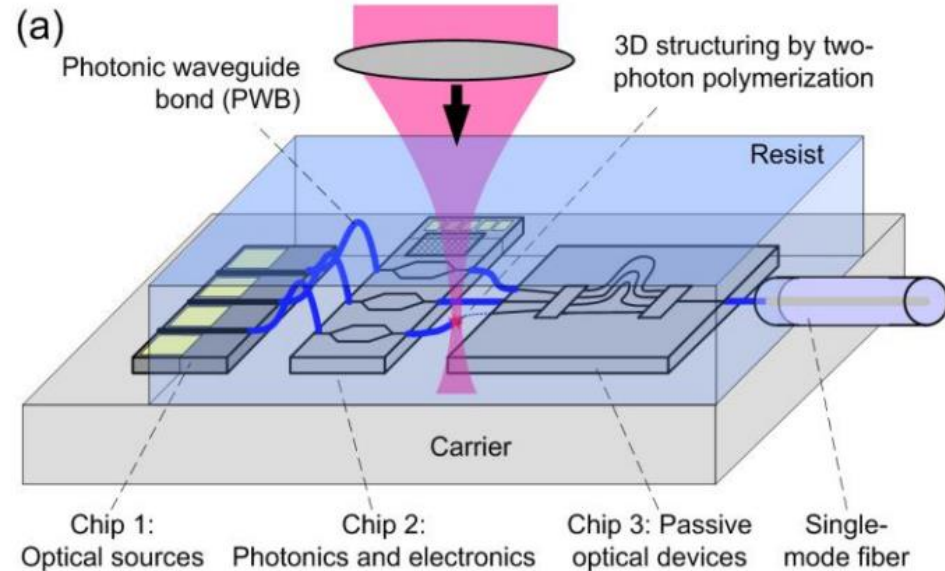
Photonic Waveguide Bonds – Chip-to-Chip Int.



nanoscribe

Optical Interconnects:

- Novel concept of chip-to-chip optical interconnect
- Optical analog to electrical wire bonds of electrically integrated circuits (IC)
- Experimental results on data rates in information processing: 5.25 Tbit/sec
- BMBF funds project „Phoibos“ with ~2.9 Mio Euros

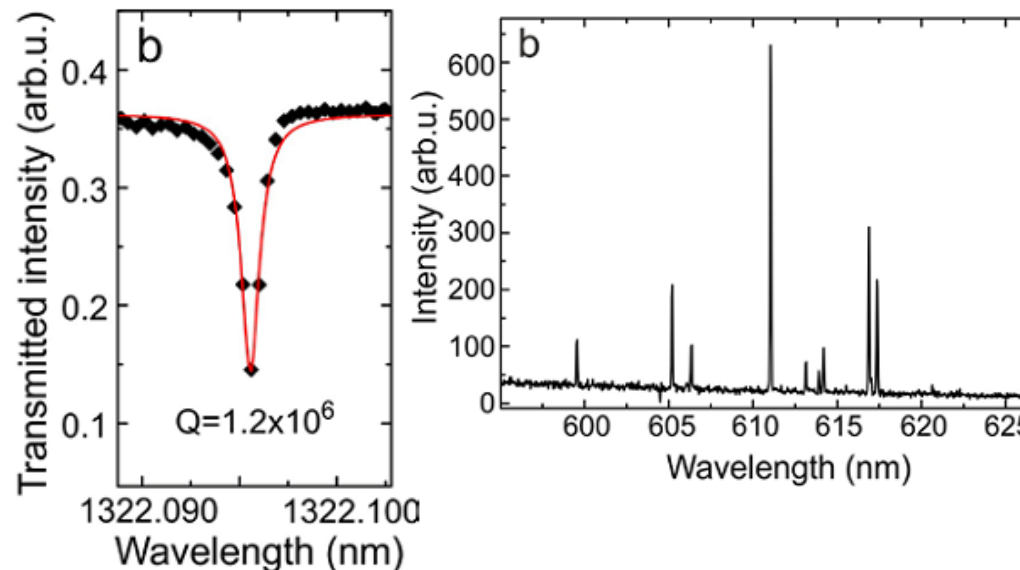
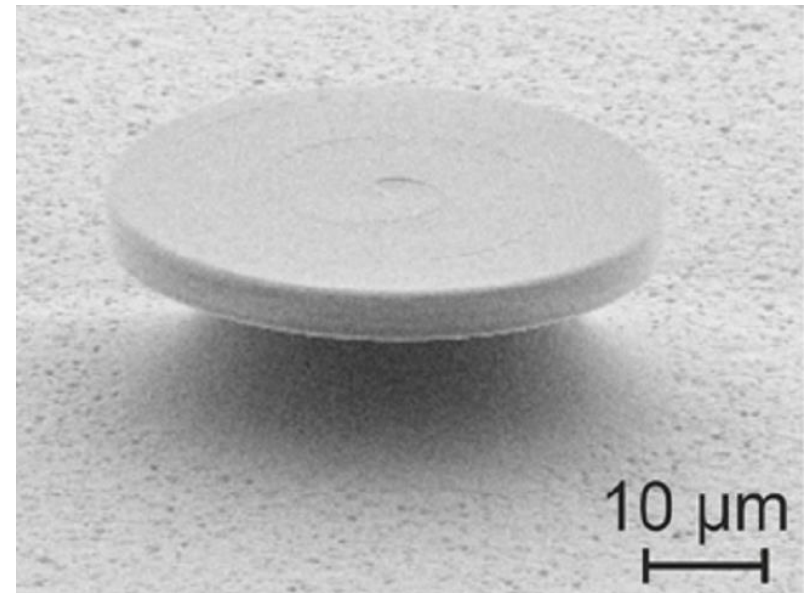




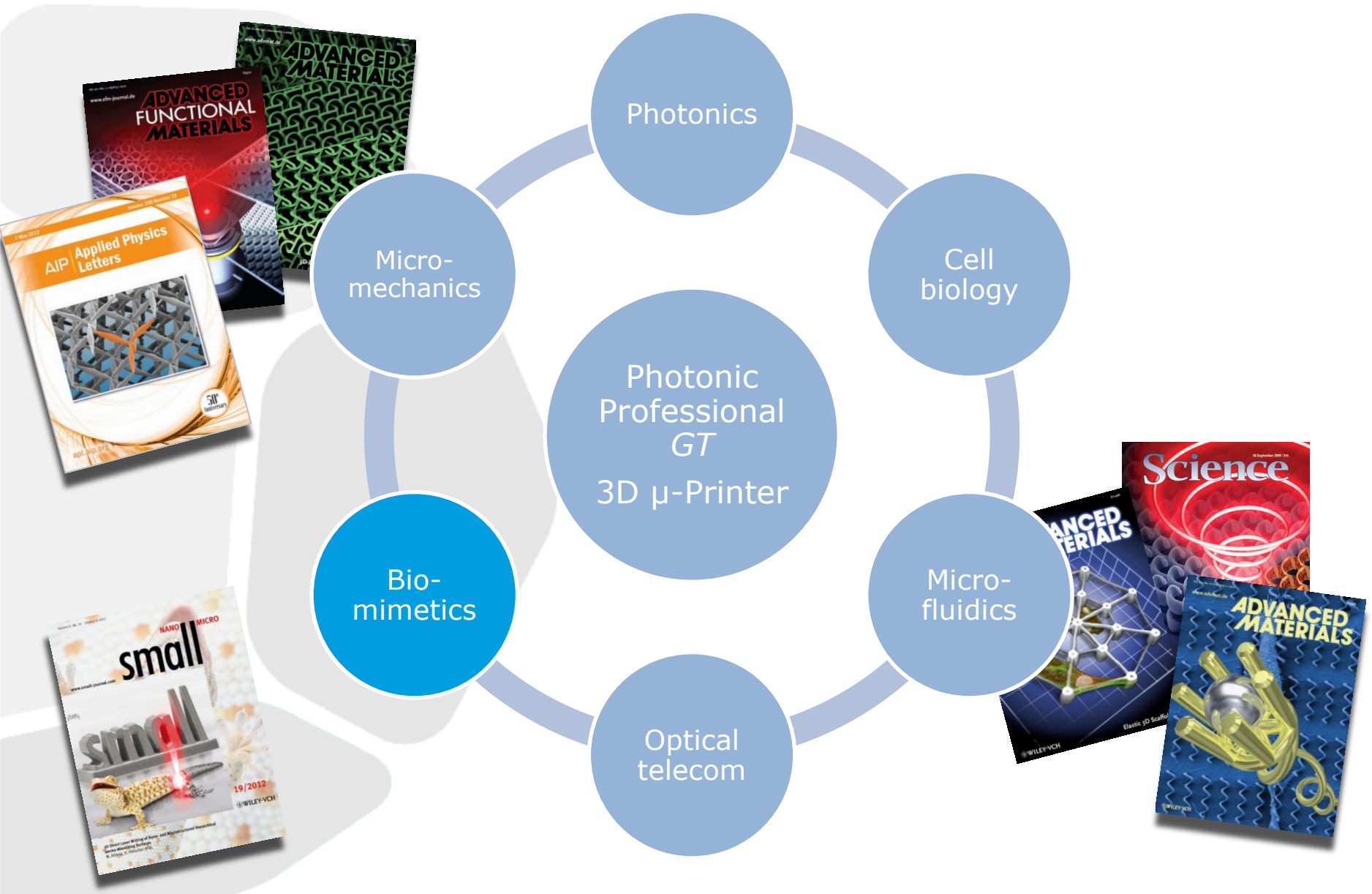
High-Q-Polymer Microdisks: Active & Passive

- High-Q passive microdisks for sensing applications with $Q=1.2 \times 10^6$
- Dye-doped microdisk laser
- Material: ORMOCOMP®
- Laser dye: Pyrromethene 597

**Complete flexibility
in cavity design**



Applications



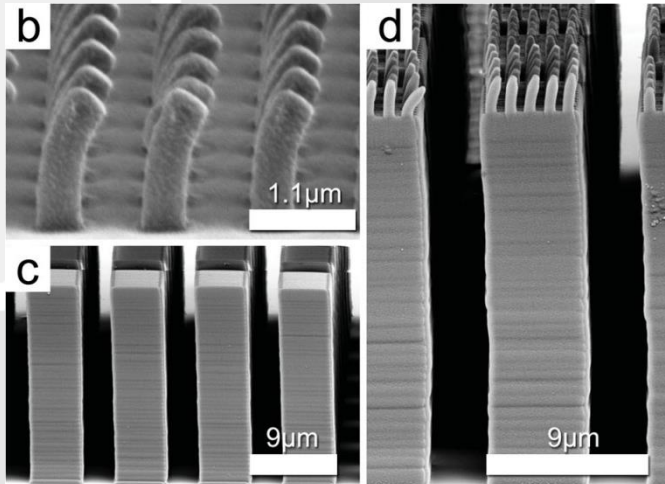
New fields – Biomimetics

Salvinia effect:

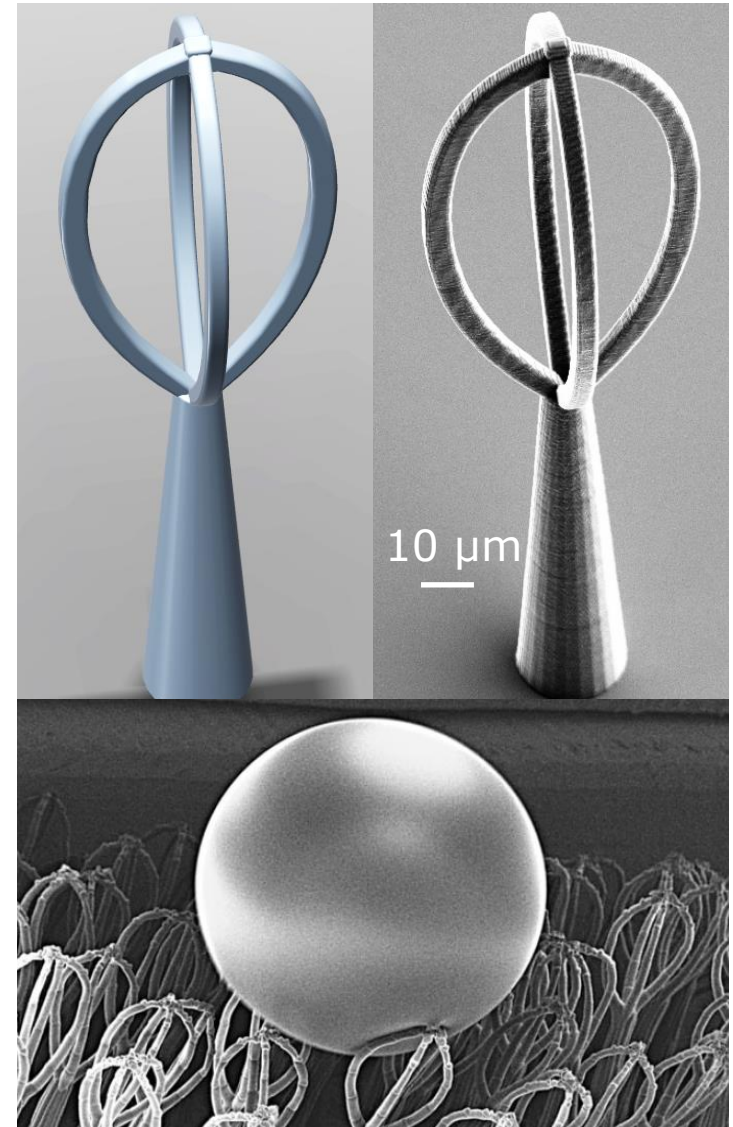
- Floating fern
- Air retention prevents getting moldy when drowned under water
- Application: Friction reduction of ships

Gecko effect:

- Application: Adhesion based on hierarchical structure

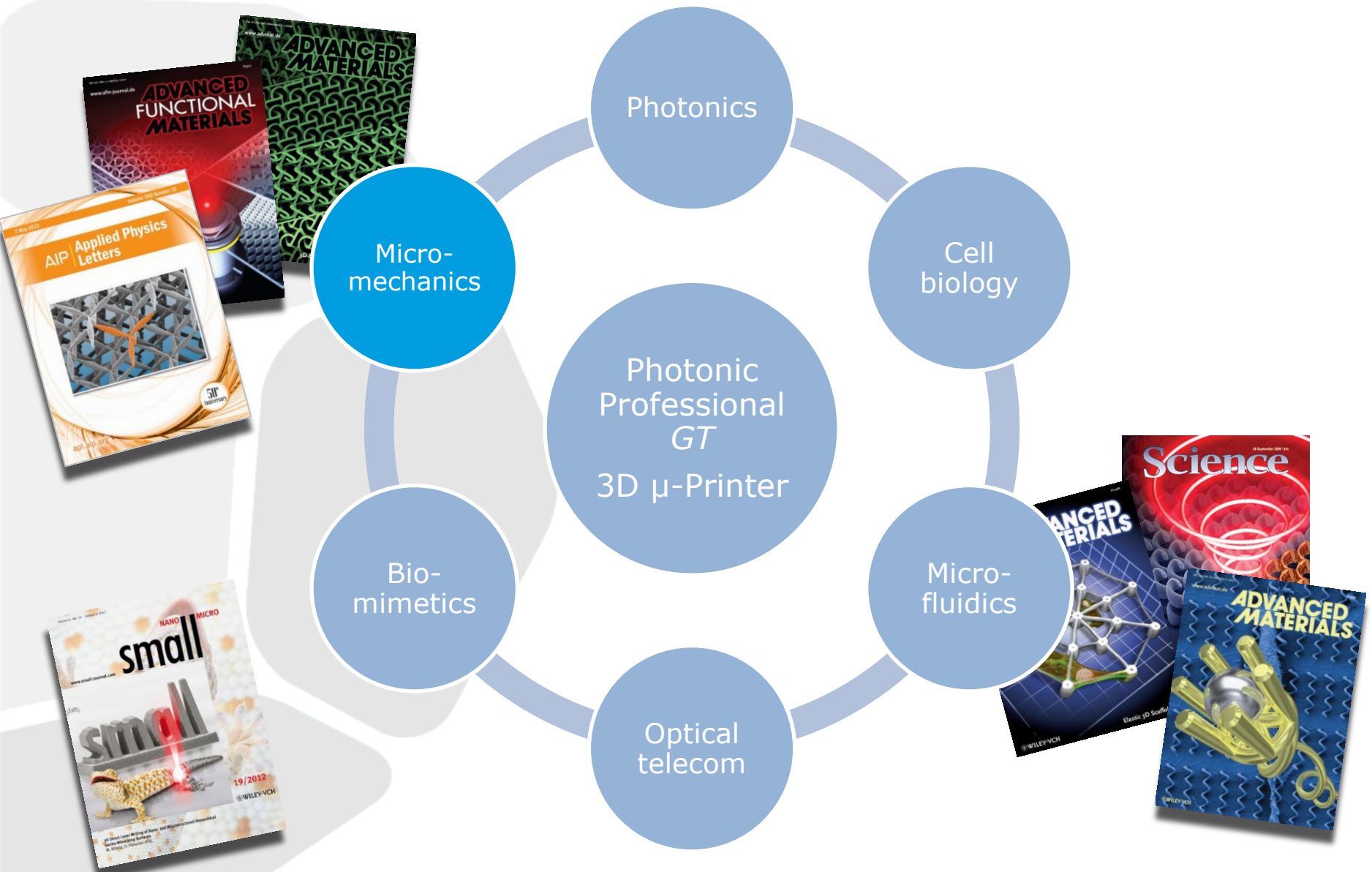


M. Röhrig *et. al.*, Small 19, 2918 (2012)



W. Barthlott, *et al.* Adv. Mater. 22, 2325 (2010)

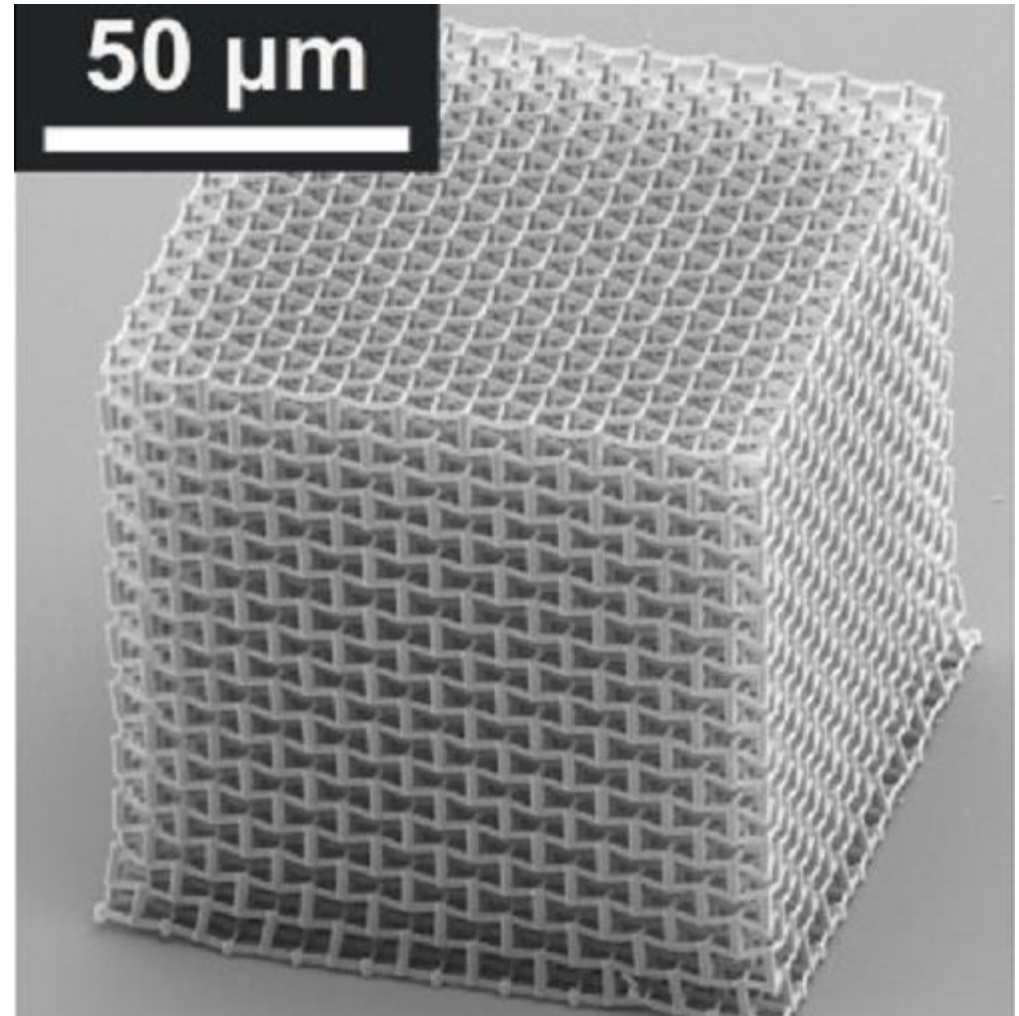
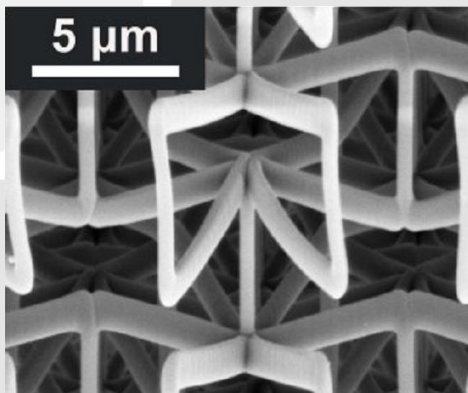
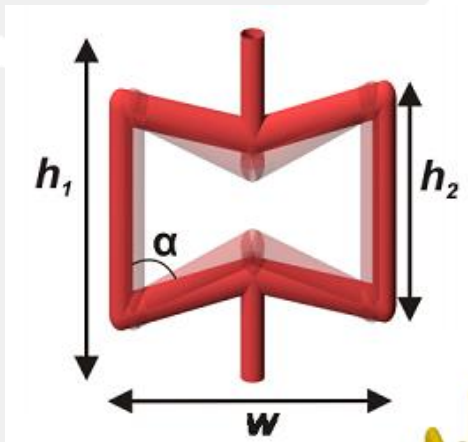
Applications



Mechanical Metamaterials

Auxetics:

- Tunable Poisson's ratio ν
- $-0.12 < \nu < +0.13$

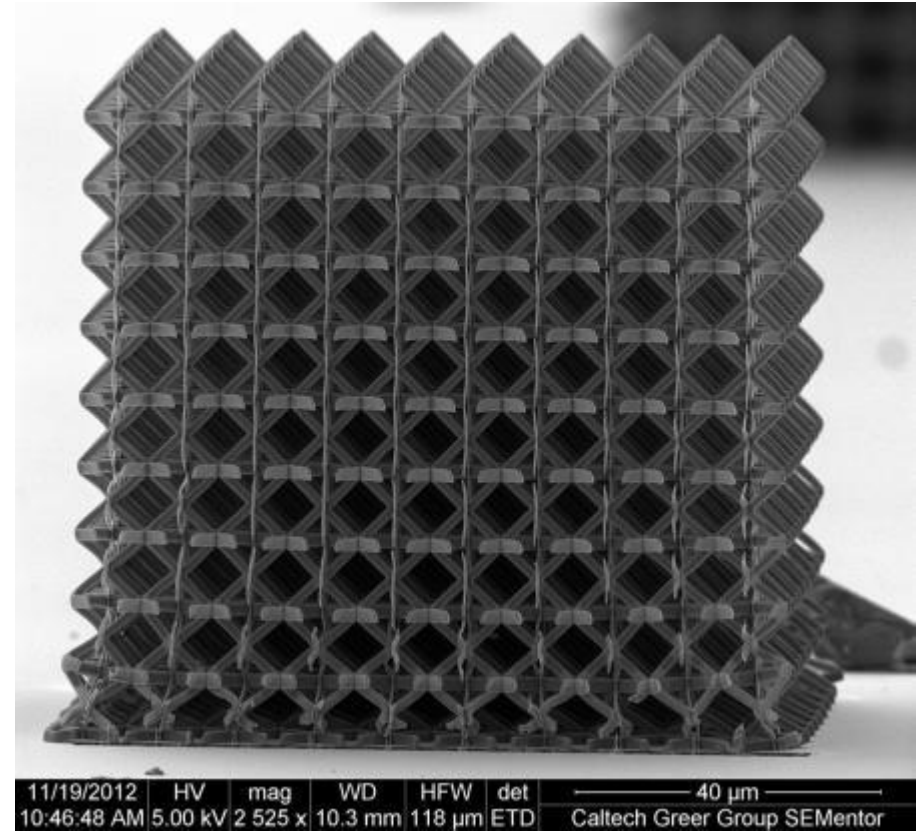
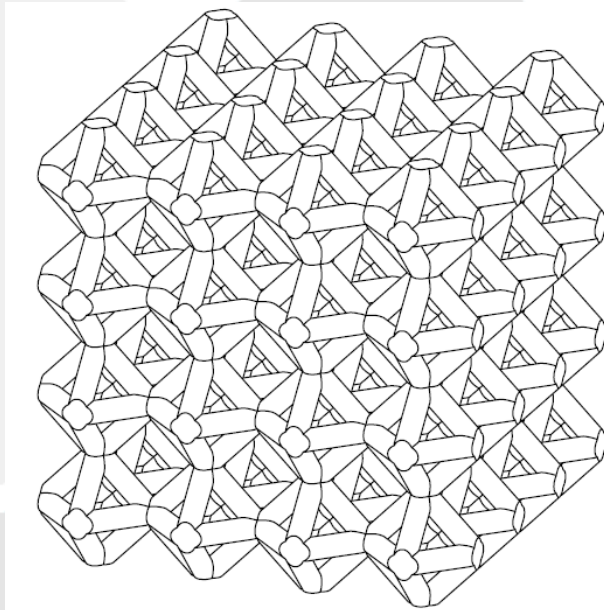


T. Bueckmann et al., Advanced Materials 24, 2710 (2012)

Ultralight Microlattices

Applications:

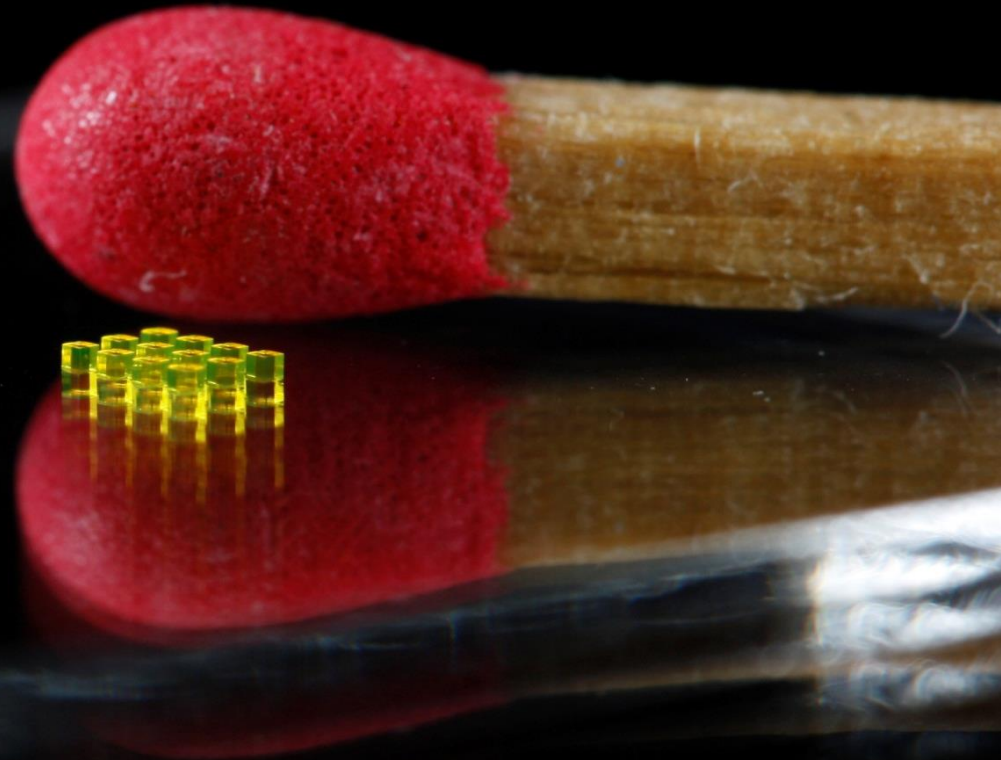
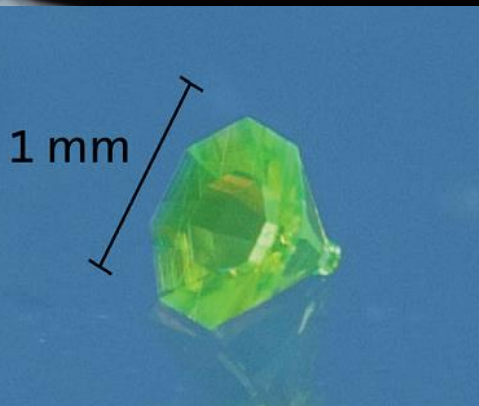
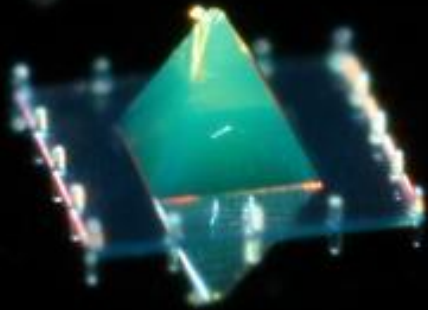
- Thermal insulation
- Battery electrodes
- Acoustic/vibration/shock damping



J. R. Greer et al., Nature Materials,
DOI: 10.1038/NMAT3738 (2013)

Macro Scale Objects for MEMS

**PRISM
AWARDS
FINALIST**



Soon coming up @ Photonics West 2014:

- STED-inspired Dip-in lithography...
- Towards larger printing volumes...

Our Team



Summary – 3D μ -Printing

